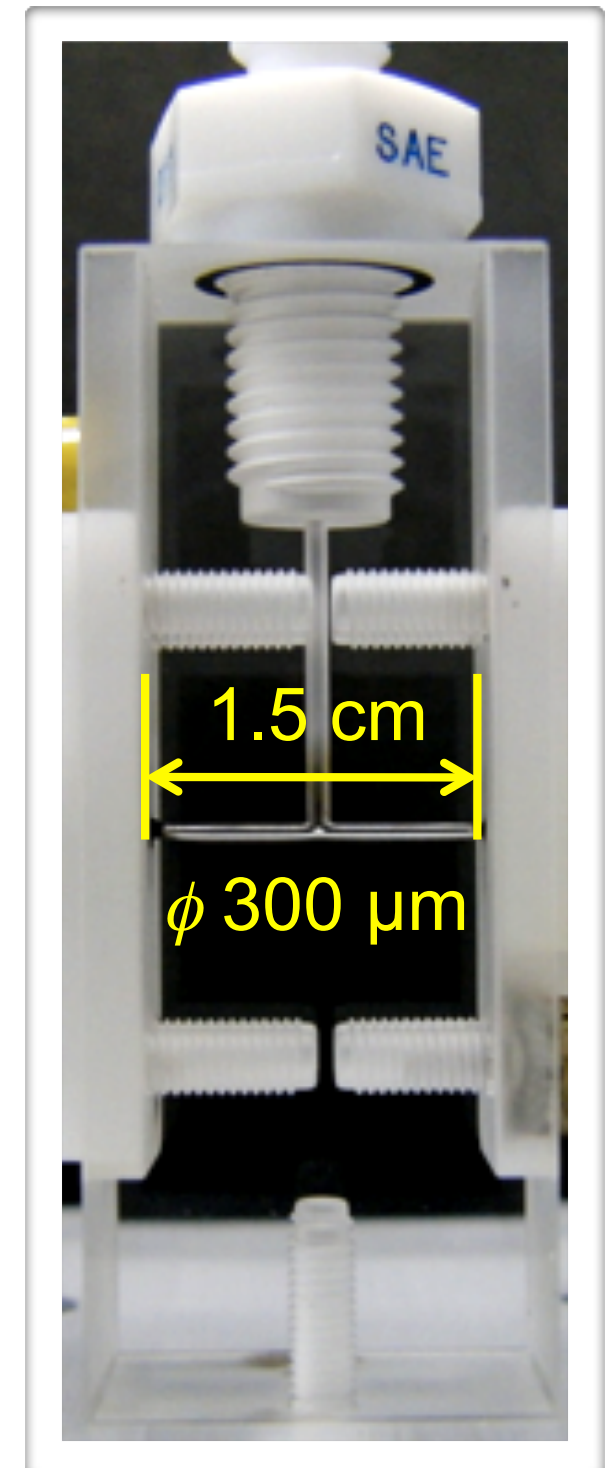
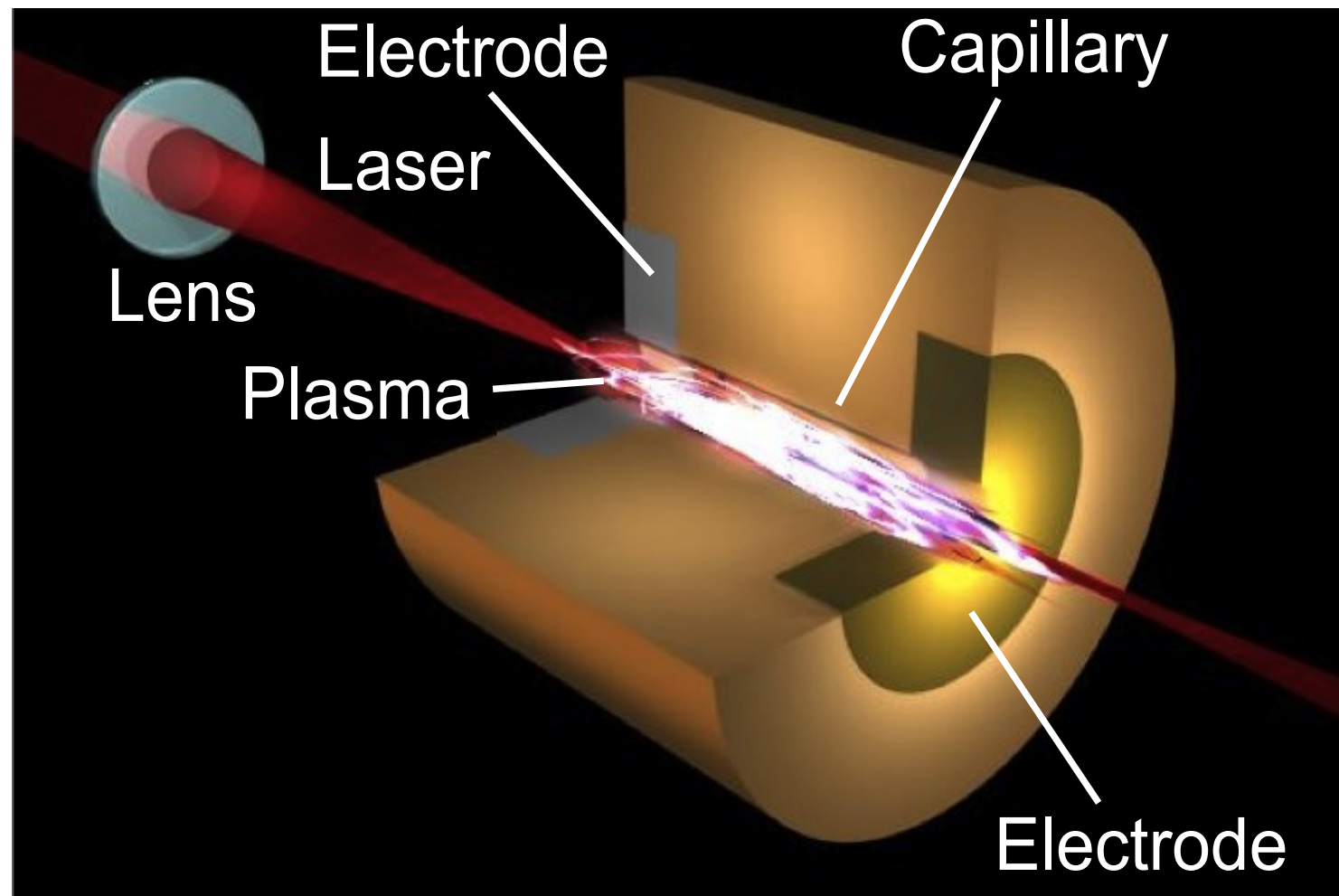




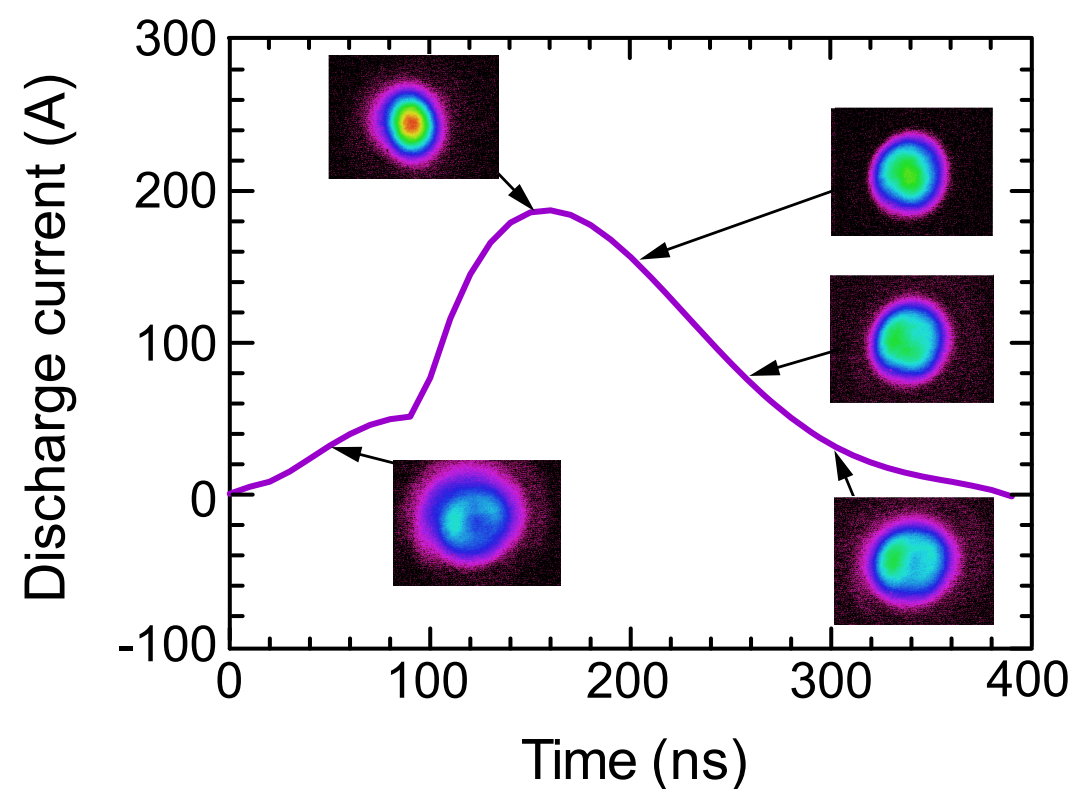
高原子番号物質プラズマによる UTA EUV光源

東口 武史

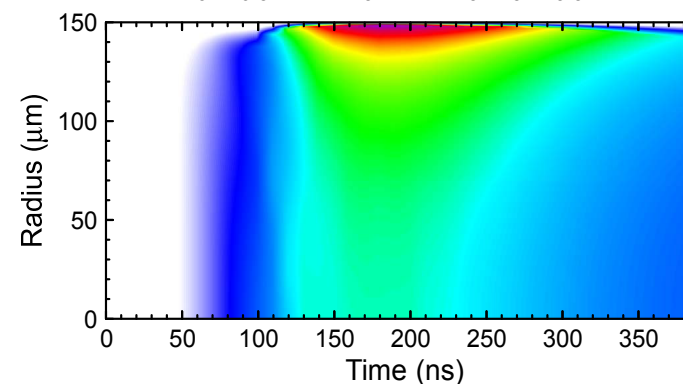
Recent Progress: Hydrogen & Argon Capillary for LWF & SXR



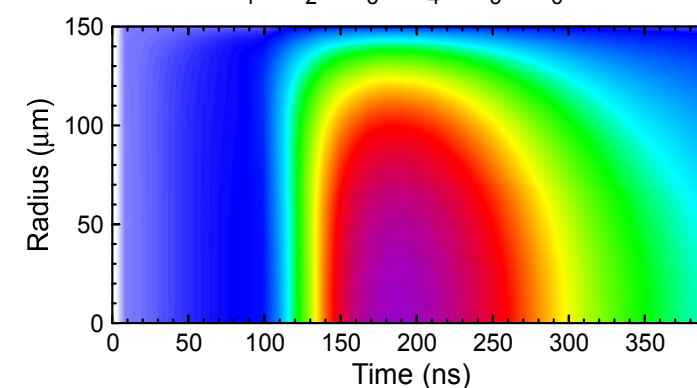
Recent Progress: Hydrogen & Argon Capillary for LWF & SXR



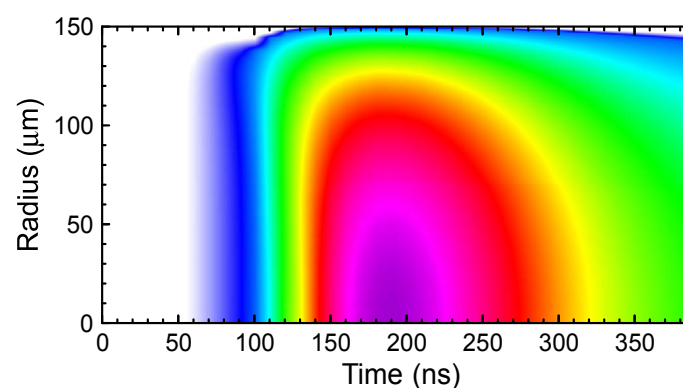
(a) density



(b) temp.

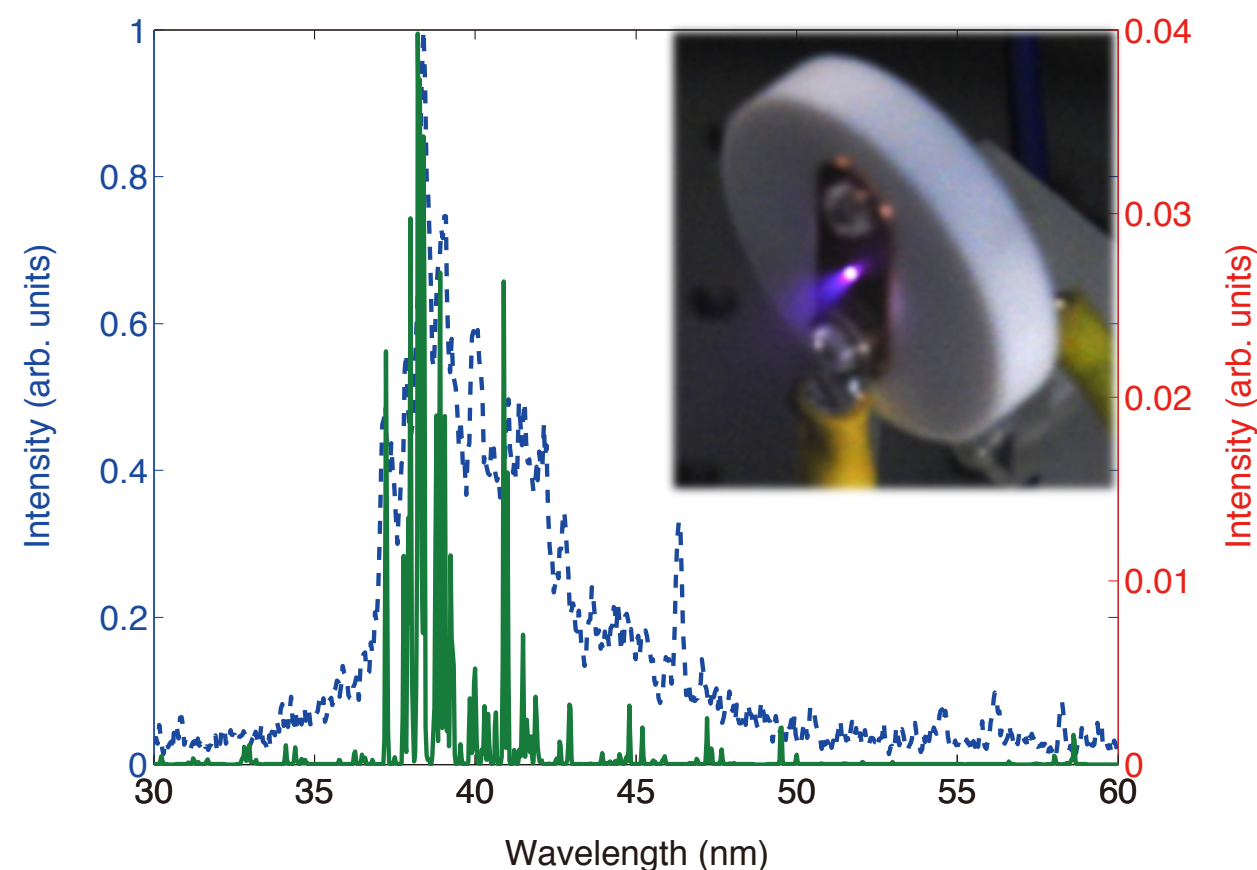
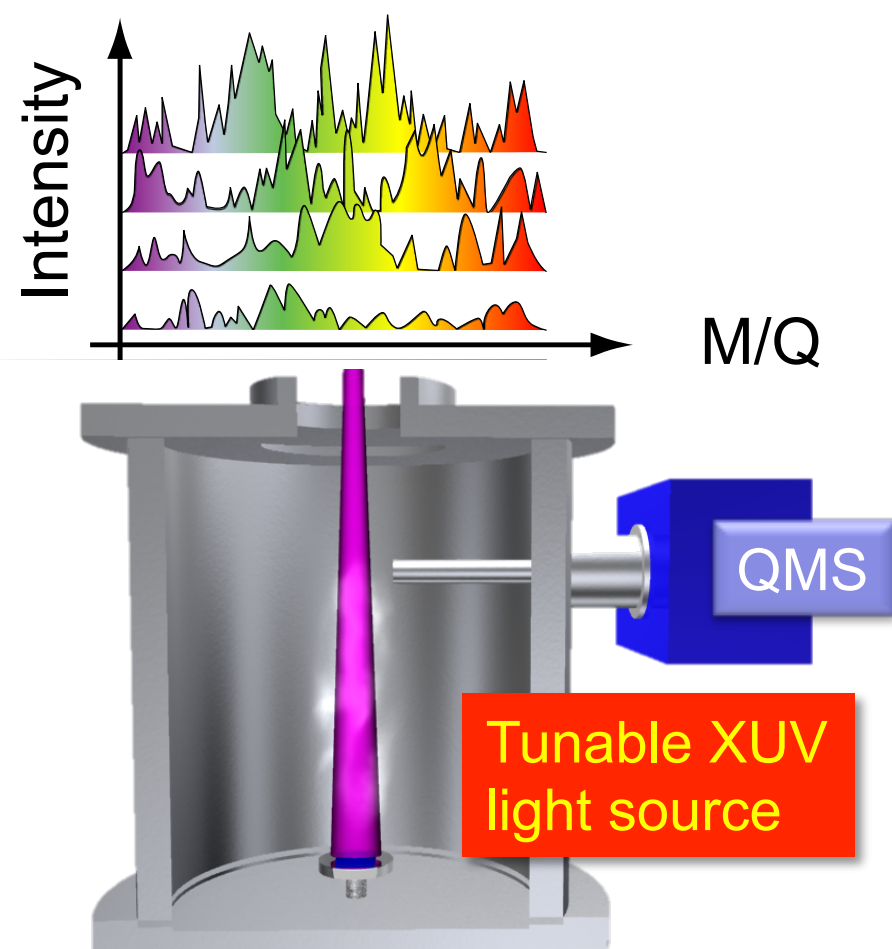


(c) Z

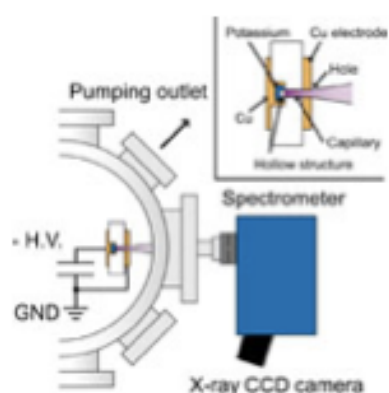


- [1] T. Higashiguchi *et al.*, Rev. Sci. Instrum. **81**, 046109 (2010).
- [2] H. Terauchi *et al.*, J. Appl. Phys. **109**, 053304 (2011).
- [3] S. Sakai *et al.*, Rev. Sci. Instrum. **82**, 103509 (2011).
- [4] T. Higashiguchi *et al.*, J. Appl. Phys. **111**, 093302 (2012).

Recent Progress: 40-nm source for mass spectroscopy



Research Highlights



Microdischarge extreme ultraviolet source with alkali metal vapor for surface morphology application

Takeshi Higashiguchi, Hiromitsu Terauchi, Takamitsu Otsuka, Mami Yamaguchi, Keisuke Kikuchi, Noboru Yugami, Toyohiko Yatagai, Wataru Sasaki, Rebekah D'Arcy, Padraig Dunne, and Gerry O'Sullivan

We have characterized a discharge-produced potassium plasma extreme ultraviolet (XUV) source. This compact capillary XUV source with a photon energy of 30 eV is a useful XUV emission source for surface morphology applications.

[Compact discharge source]

T. Higashiguchi *et al.*, Appl. Phys. Lett. **96**, 131505 (2010).
T. Higashiguchi *et al.*, J. Appl. Phys. **109**, 013301 (2011).

[Temporal behavior]

T. Higashiguchi *et al.*, Appl. Phys. Lett. **98**, 091503 (2011).
T. Higashiguchi *et al.*, J. Appl. Phys. (submitted in 2012).

Recent Progress: **W** plasma spectroscopy in **LabTalk, IOP/JPB**



Journals ▾ | Login ▾



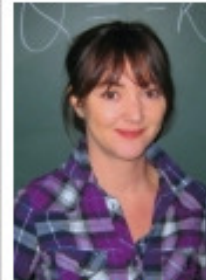
C S Harte



T Higashiguchi



T Otsuka



R D'Arcy



D Kilbane



G O'Sullivan

Journal of Physics B: Atomic, Molecular and Optical Physics

Tungsten spectroscopy for magnetic fusion

Understanding the radiative properties of tungsten is vital for the success of ITER.

The first ITER plasma is due in 2019 and this plasma, like every future one, will contain tungsten as an intrinsic impurity since tungsten has been chosen as a plasma facing component due to its high melting point and low erosion properties. The presence of tungsten in a hot plasma may present a problem in terms of radiation losses in the EUV region but studying this emitted light will provide crucial plasma diagnostic information. However, the EUV radiation emitted from moderately ionized tungsten (W^{12+} – W^{37+}) is complex and does not usually take the form of isolated lines but of transition arrays and a lack of definitive data makes interpretation of spectra quite challenging.



Laser produced plasma at UCD.

C. S. Harte *et al.*, J. Phys. B **45**, 245004 (2012).

Requirement in high-Z plasma UTA **with high CE**

Low density, high temperature plasma

Optically thin plasmas for reducing self-absorption effects

Suppression of satellite emission & higher spectral purity

Long wavelength (low critical density): **CO₂ laser**@ 10^{19} /cc

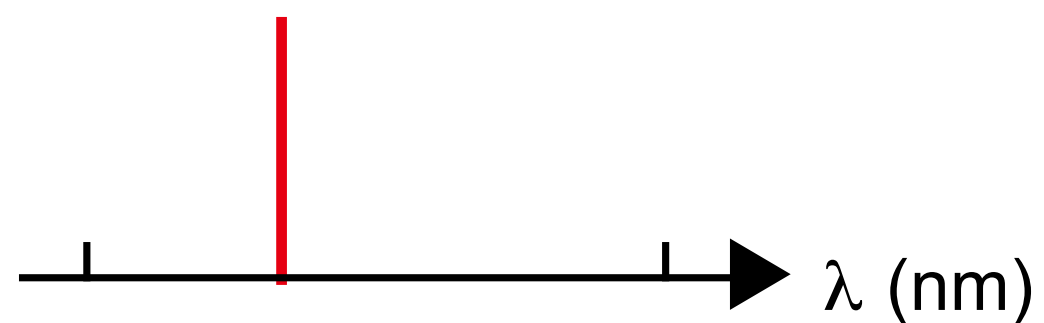
Short laser pulse duration: ~1-2 ns@YAG laser (1064 nm)

Low density targets

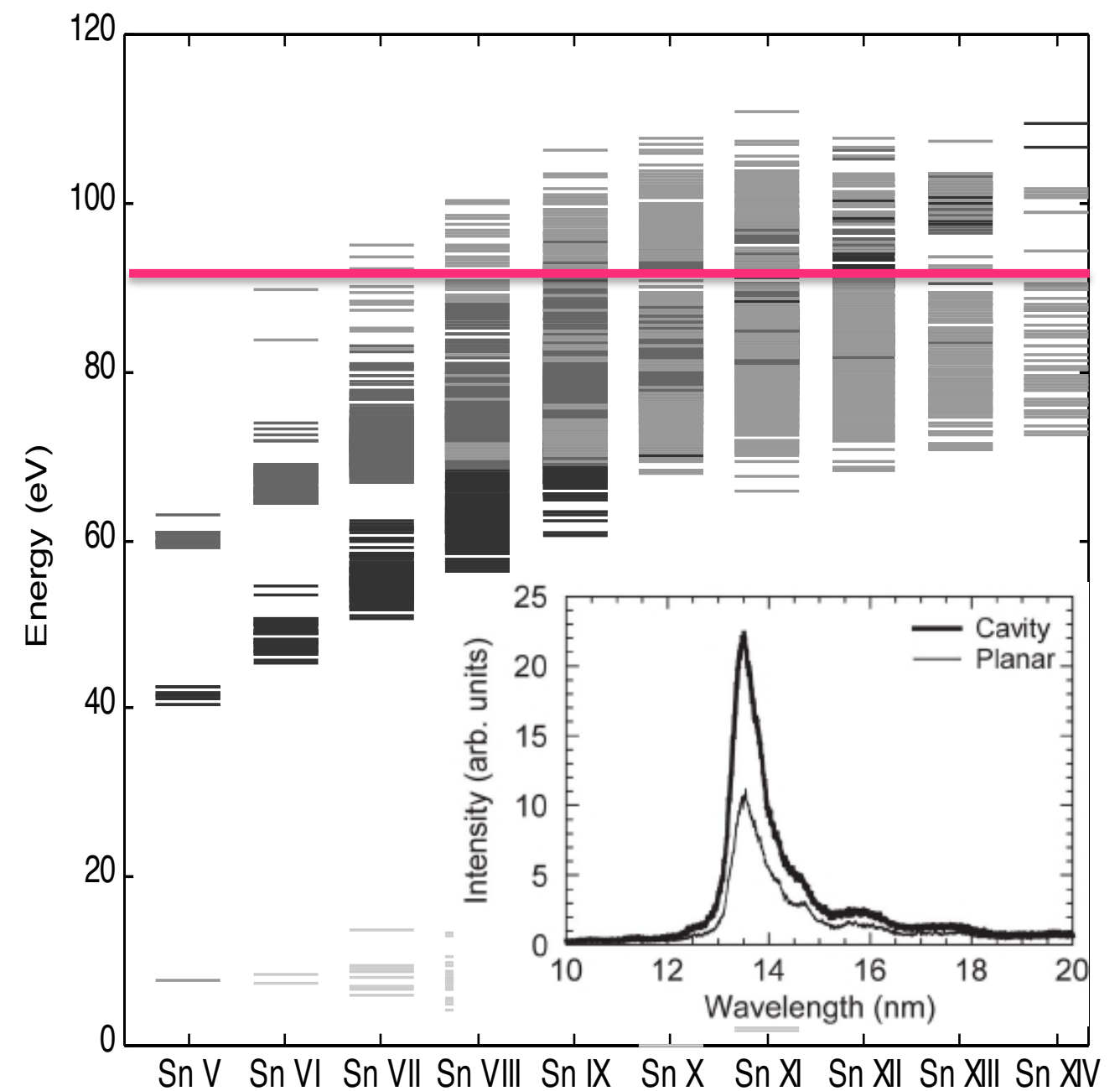
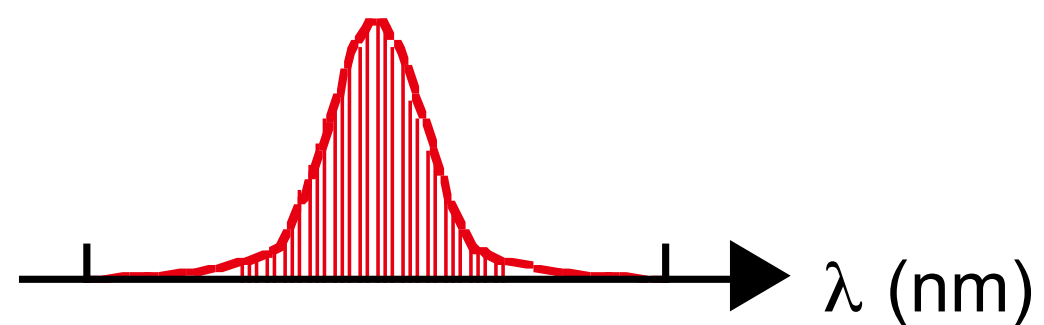
Discharge plasmas (low density plasmas)

Scheme for high-energy emission: **unresolved transition array**

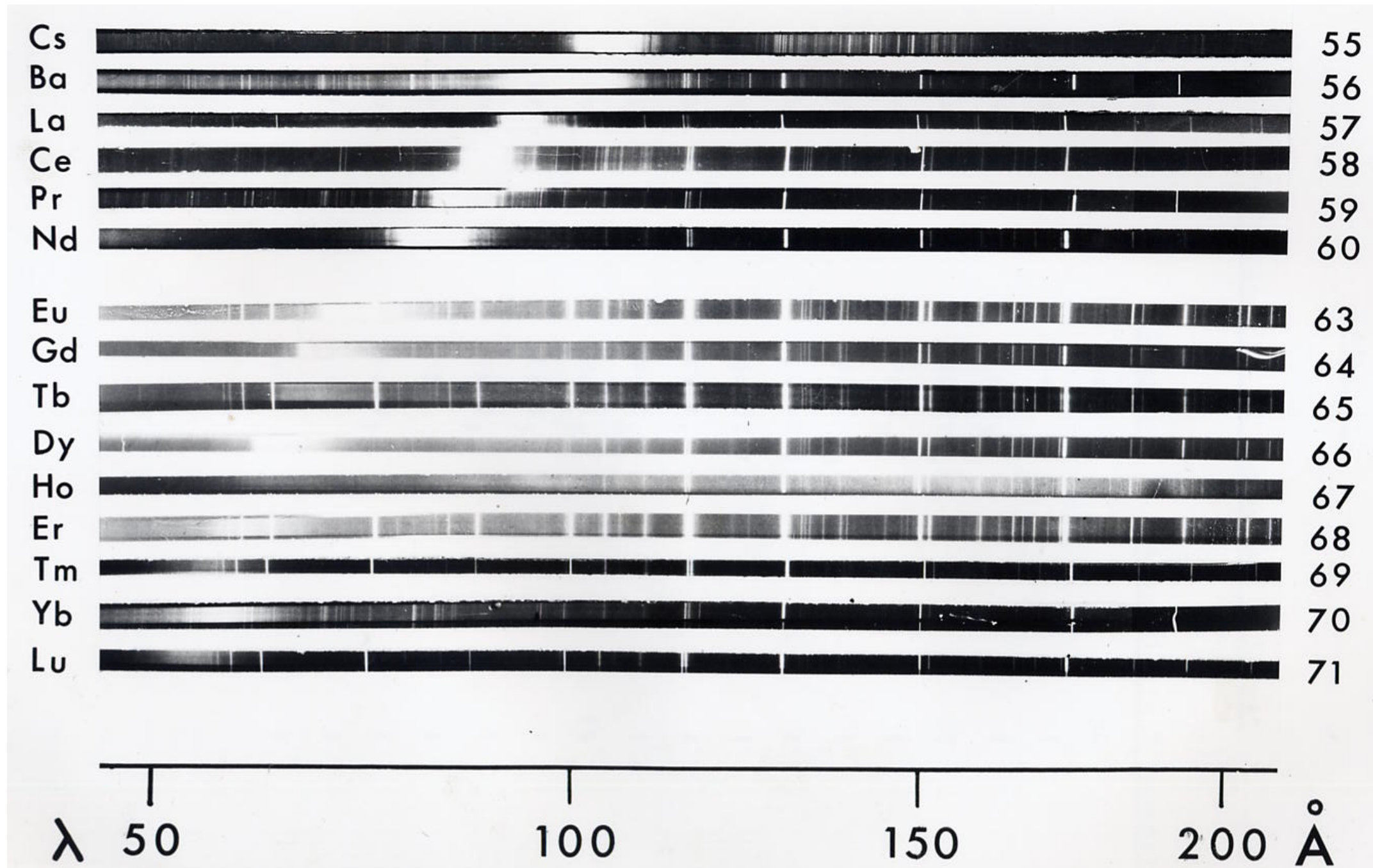
(a) Line spectrum



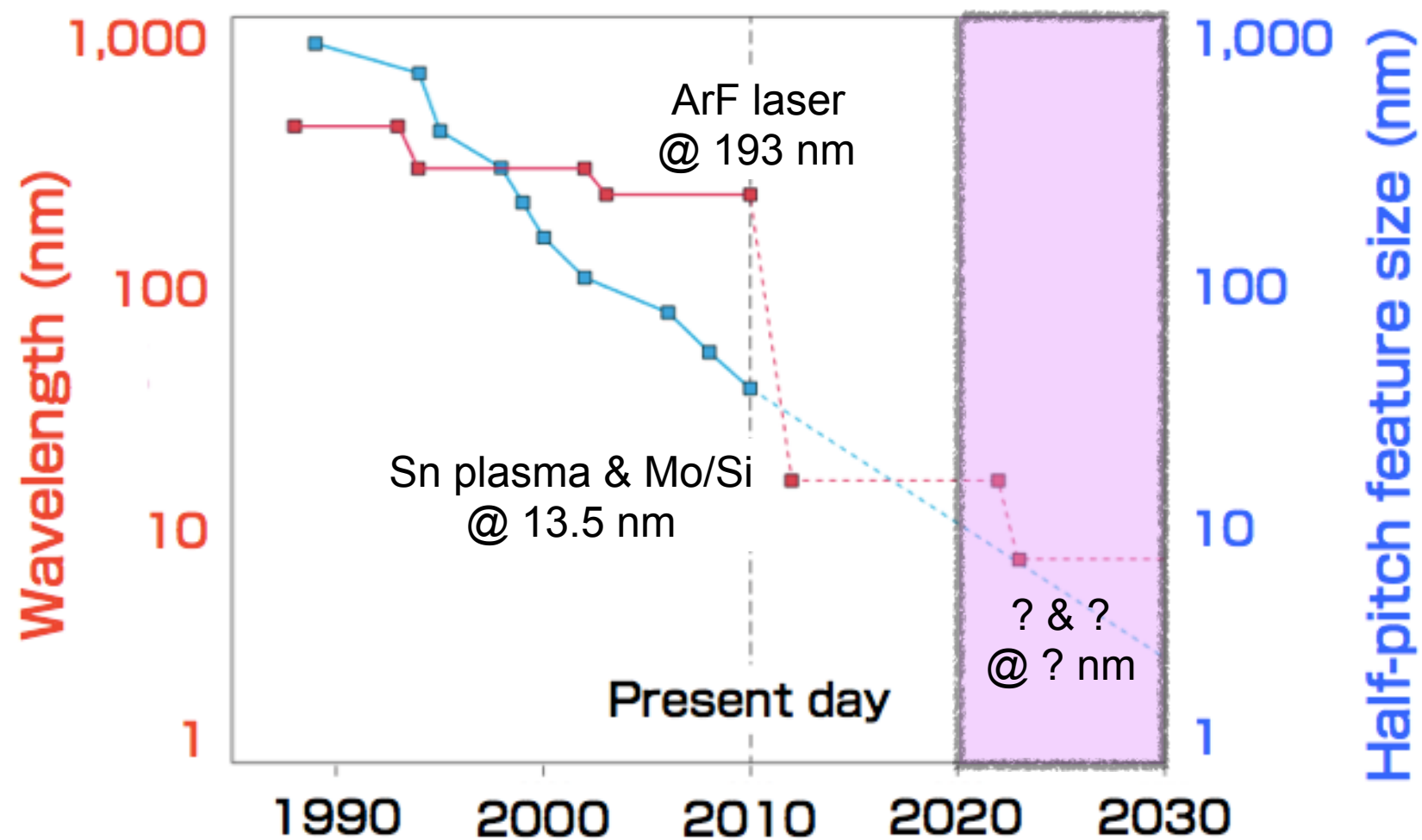
(b) UTA



Shorter wavelength emissions: **Atomic number dependence**

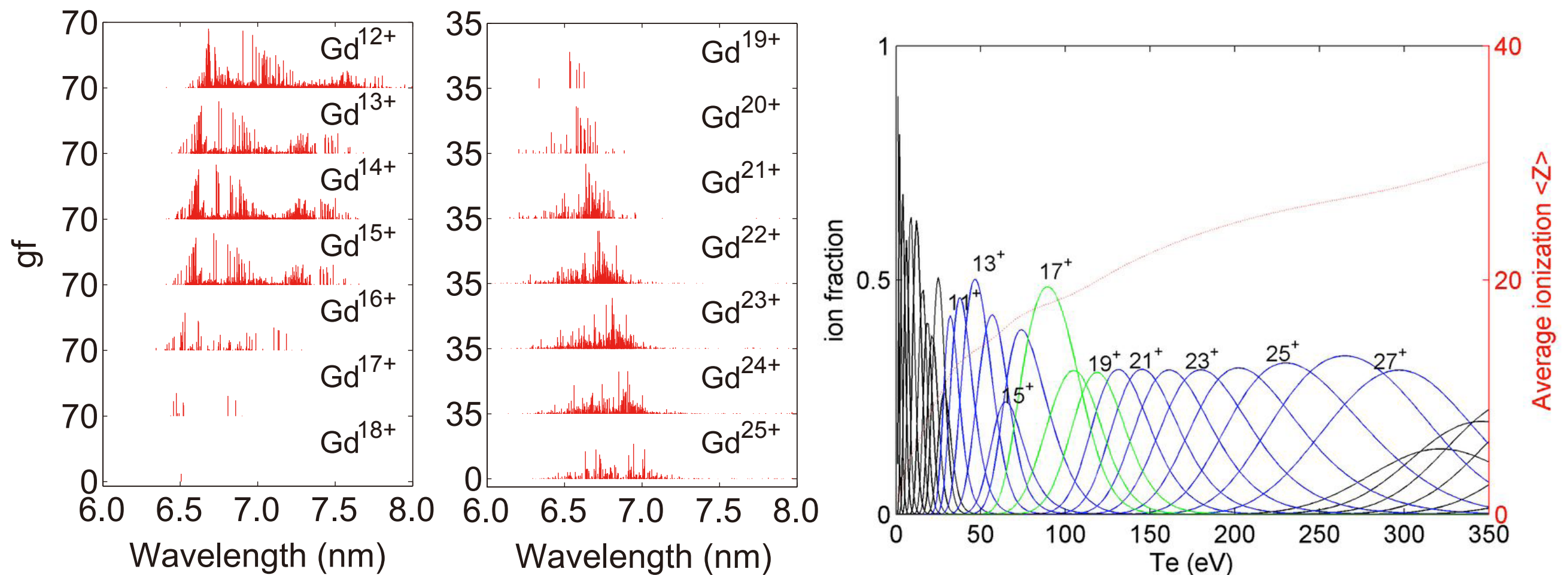


Possibility of wavelength switching



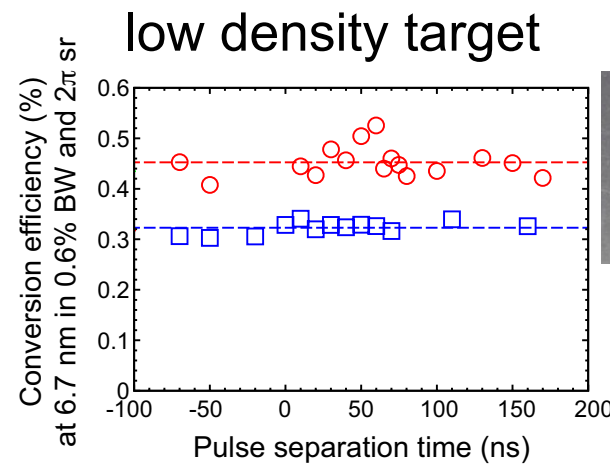
G. Tallents *et al.*, Nature Photonics **4**, 809 (2010).

Gd/Tb plasmas for 6.X-nm Beyond EUV (**BEUV**) sources

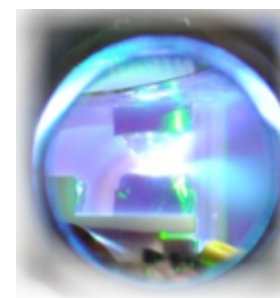
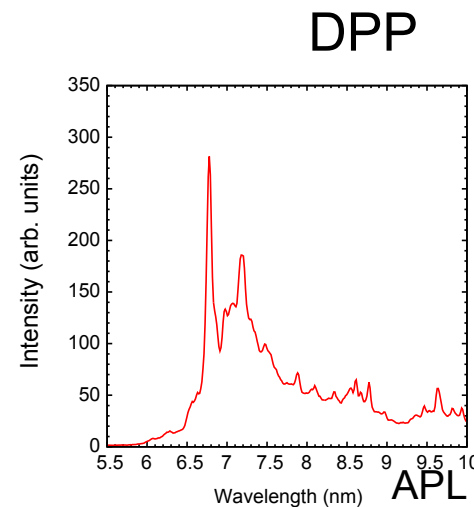


T. Otsuka *et al.*, Appl. Phys. Lett. **97**, 111503 (2010).
B. Li *et al.* Appl. Phys. Lett. **99**, 231502 (2010).

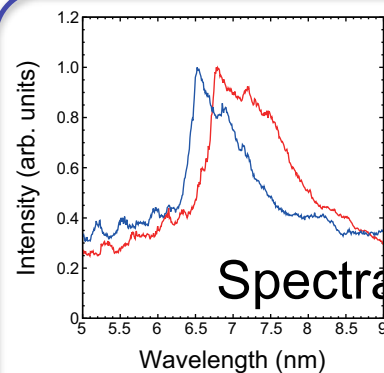
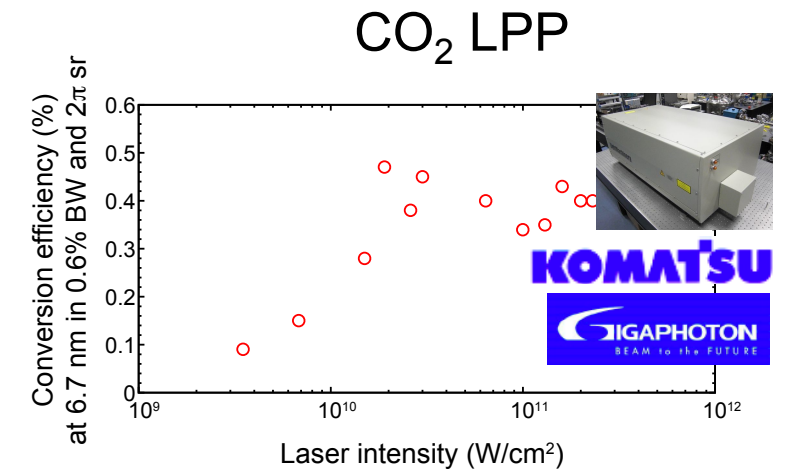
Recent Progress: 6.X-nm Beyond EUV sources



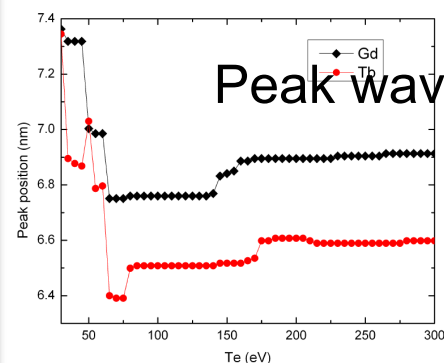
APL **99**, 191502 (2011).



APL **99**, 231502 (2010).



APL **97**, 111503 (2010).



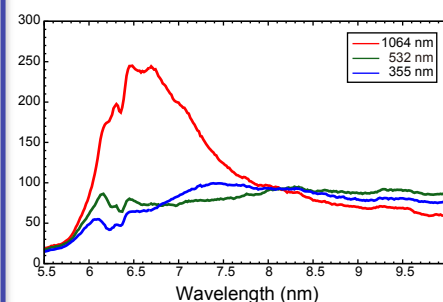
APL **101**, 013112 (2012).

$$I(\lambda)$$

$$= I_0(\lambda) e^{-\sigma n \ell}$$

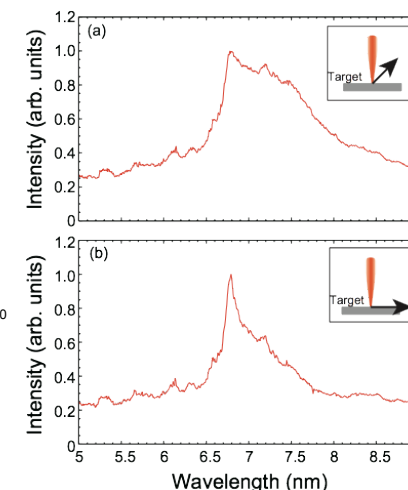
$$\ell \approx c_S \tau_L$$

Self-absorption

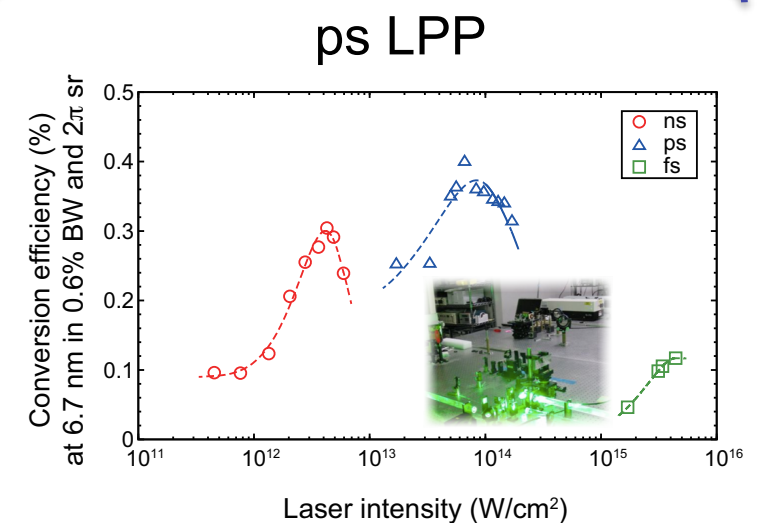


Shorter-wavelength extreme-UV sources below 10nm

APL **97**, 231503 (2010).



APL **100**, 141108 (2012).

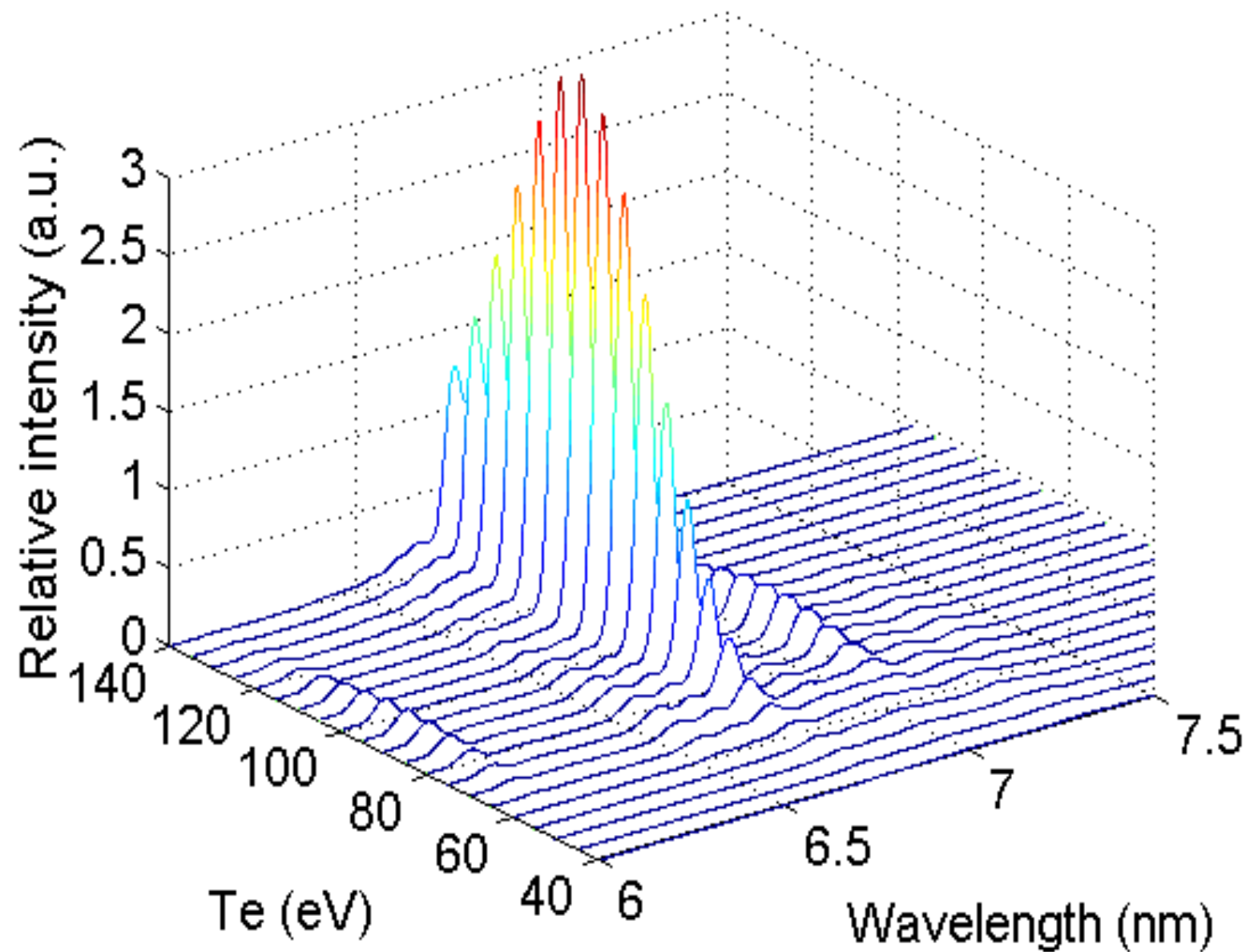


APL **100**, 061118 (2012).

BEUV Activity



Optimum condition for 6.X nm



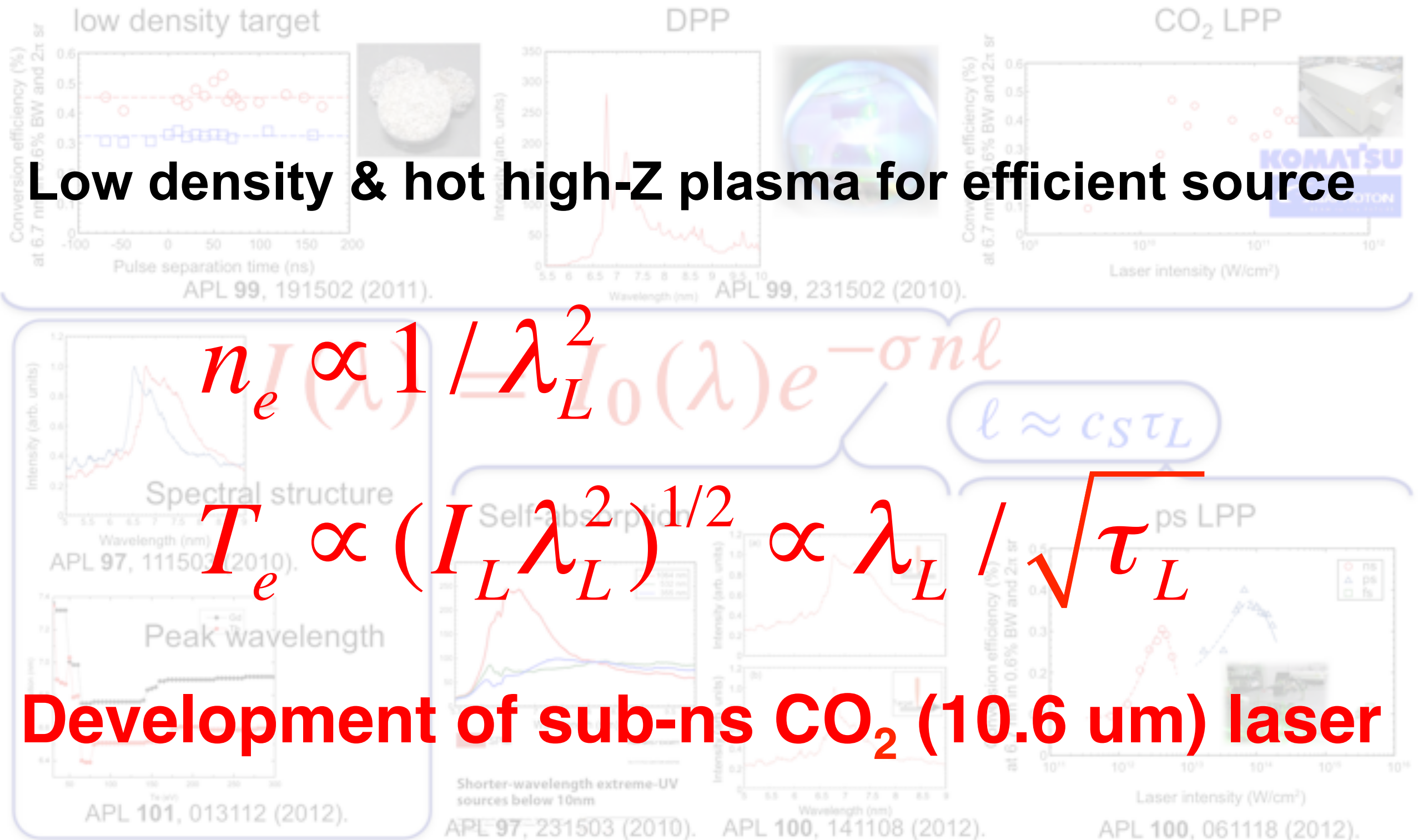
CO₂ laser intensity:

$$2.4 \times 10^{11} \text{ W/cm}^2$$

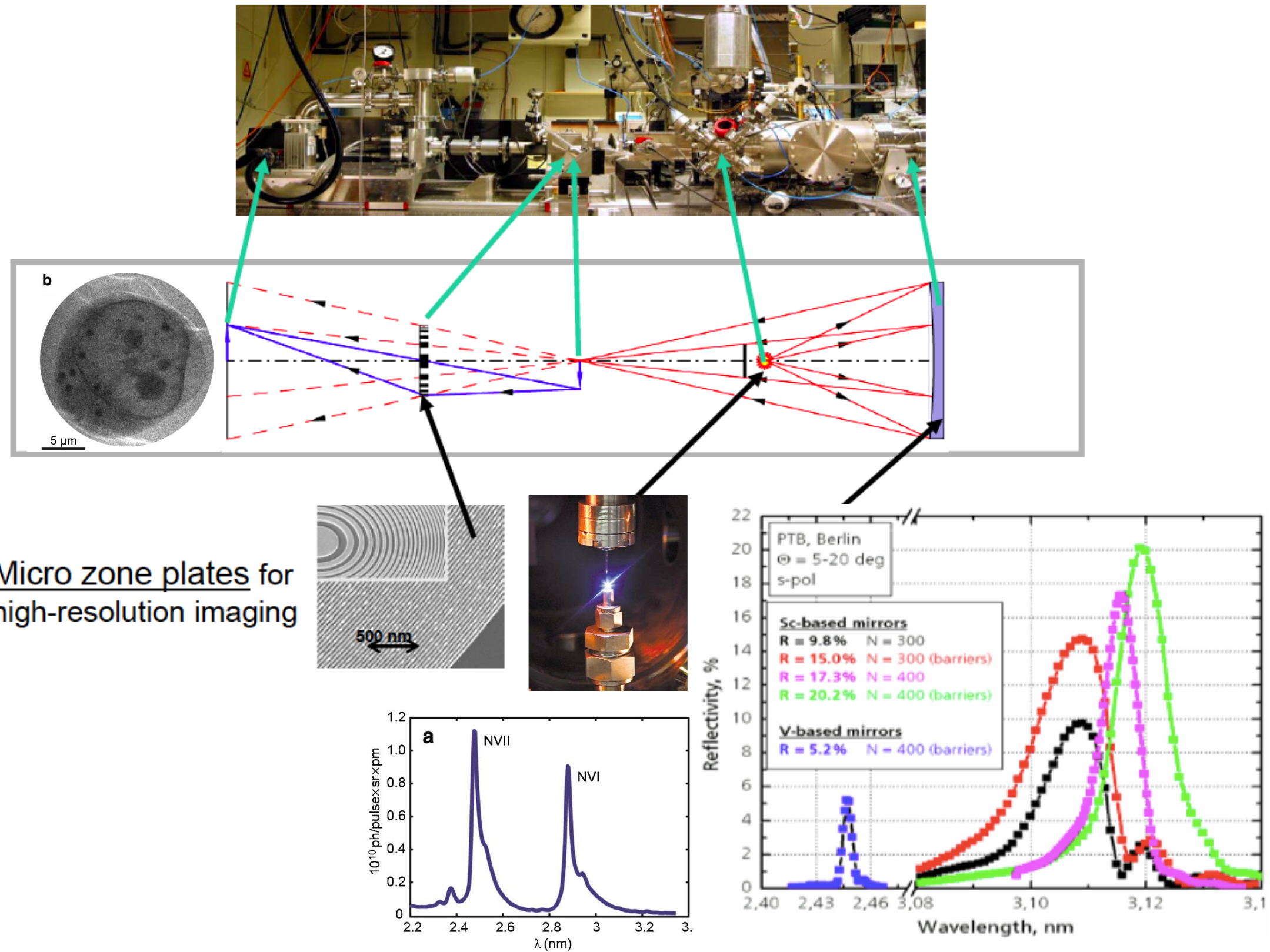
B. Li *et al.* Appl. Phys. Lett. **99**, 231502 (2010).

Why sub-ns CO₂?

Low density & hot high-Z plasma for efficient source



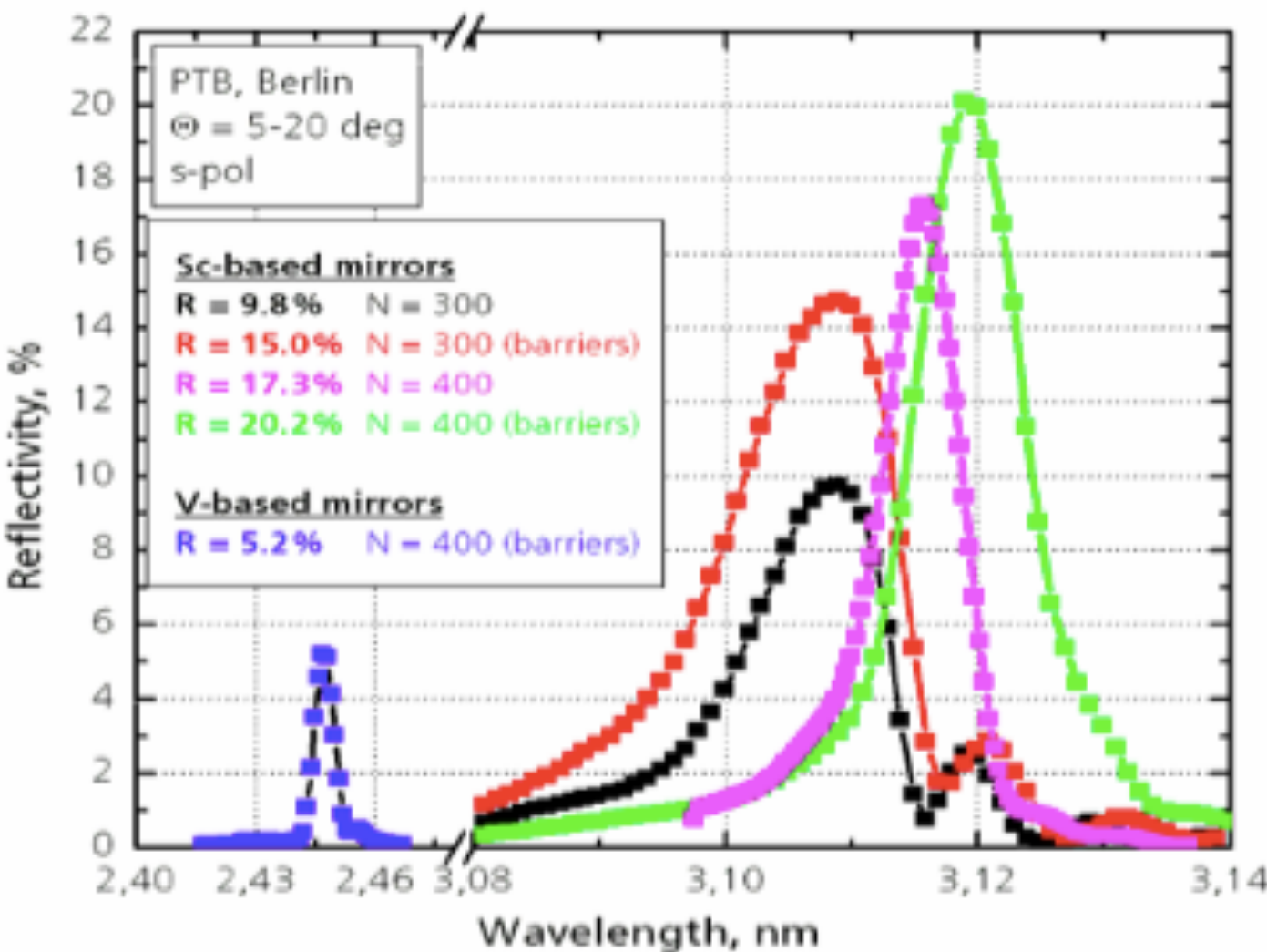
Low CE N-plasma & Low Reflectivity, resulting in **MANY SHOTS**



Multilayer Mirrors in Water Window

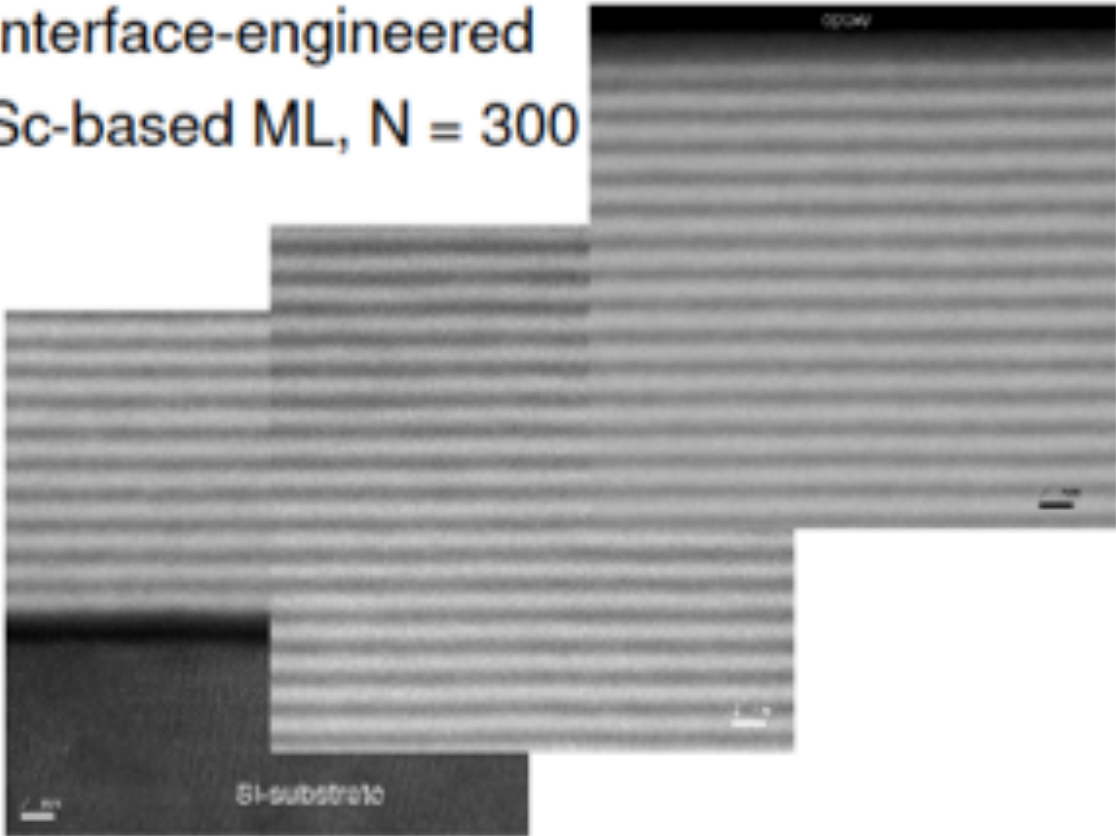
Spectral range from 2 to 5 nm

Enhanced reflectance of Sc- and V-based multilayer mirrors with interface-engineering



Multilayer	λ	N	R	FWHM
Sc - based	4.4 nm	300	7.1 %	0.021 nm
	3.1 nm	400	20.2 %	0.008 nm
V - based	2.5 nm	400	5.2 %	0.006 nm

Interface-engineered
Sc-based ML, N = 300

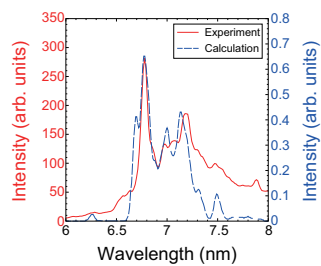
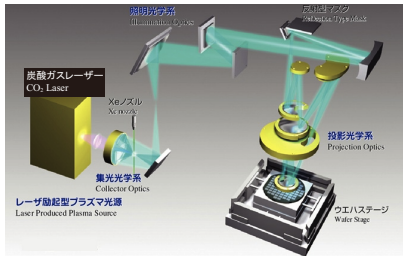


Single shot flash source in WW for Bio Photo **in LAB**

Our objective is a demonstration of high-brightness, high energy EUV/soft x-ray source in water window (3.2 nm) for the first time in the world!!!

Lithography

EUV & BEUV source study
Wavelength: 13.5 & 6.x nm

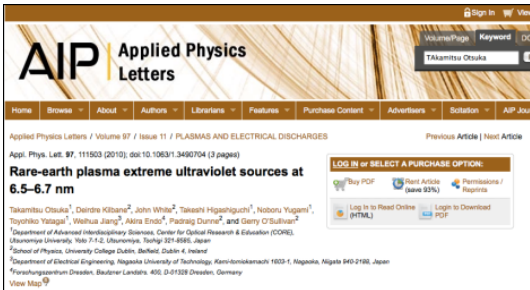


Shorter wavelength



Shorter-wavelength extreme-UV sources below 10nm

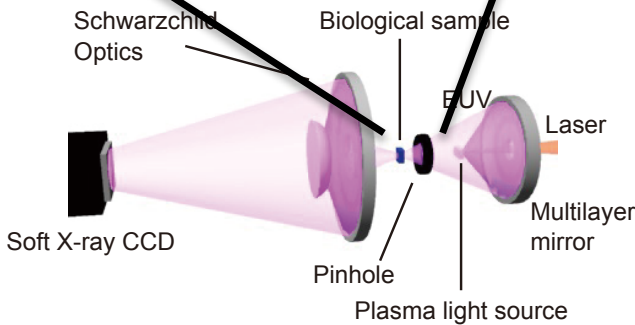
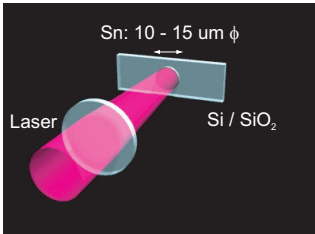
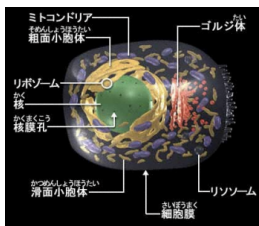
Takeshi Higashiguchi, Takamitsu Otsuka, Noboru Yugami, Weihua Jiang, Akira Endo, Padraig Dunne, Bowen Li, and Gerry O'Sullivan



Life Innovation

Compact source development for Bio.
Wavelength: 2-4 nm

In vivo cell observation Original micro source



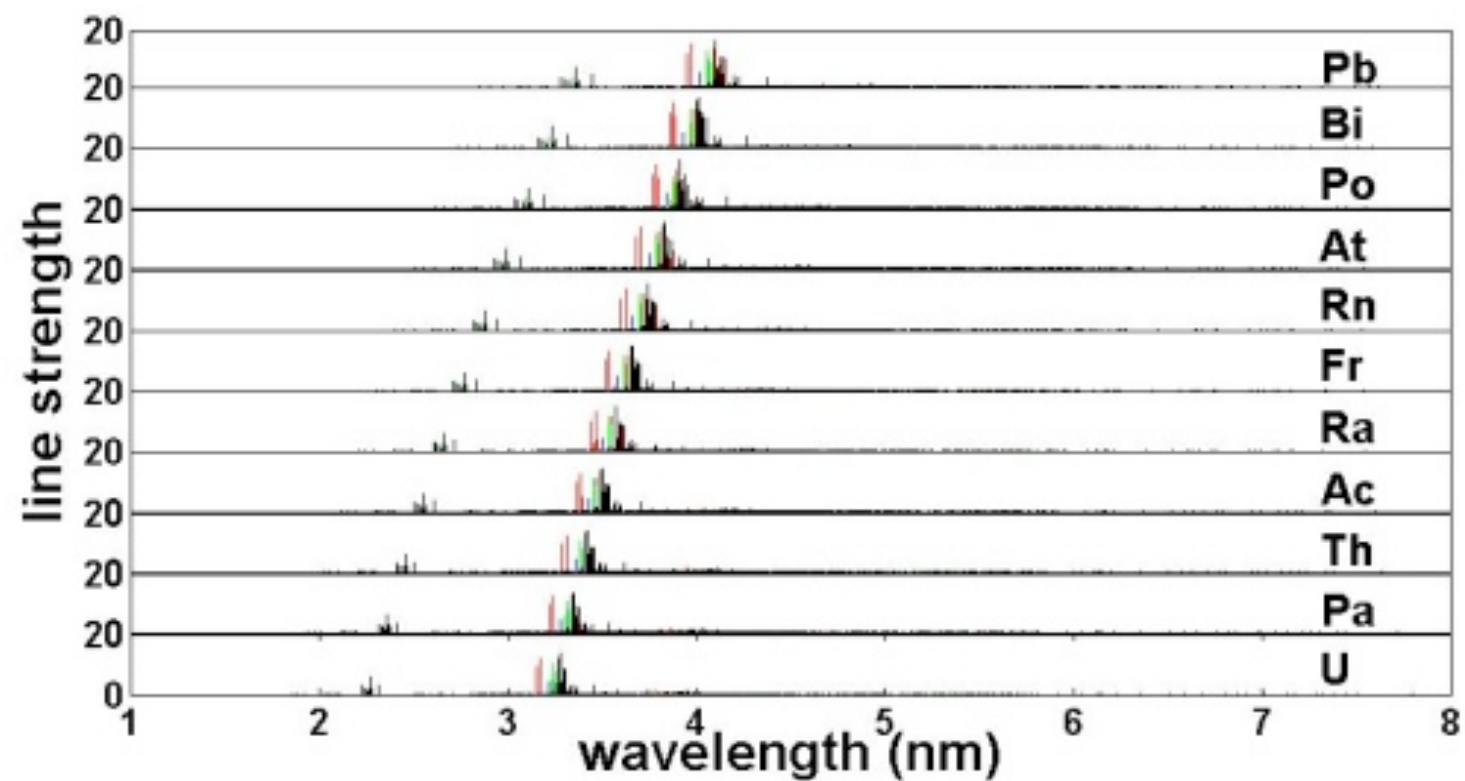
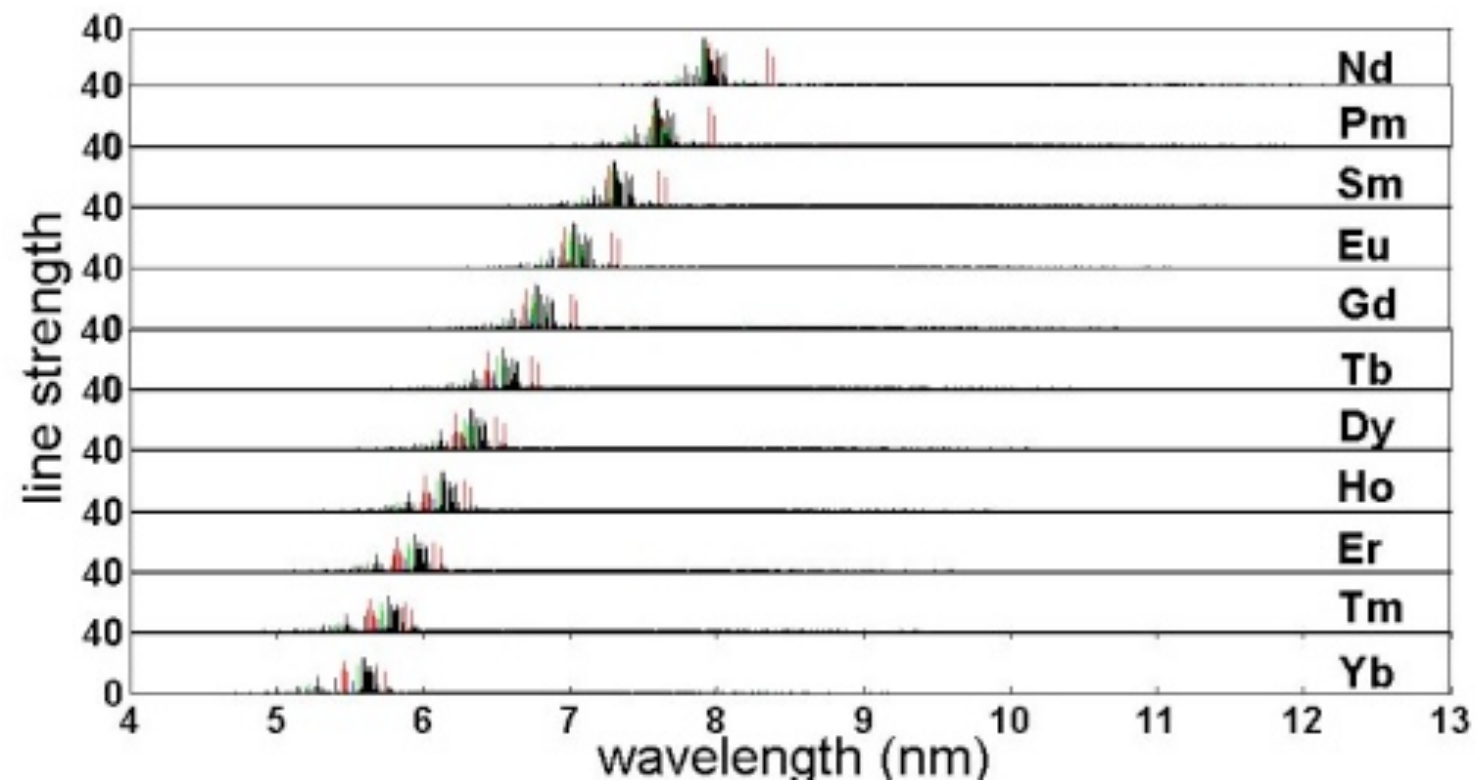
Single shot, flash biological imaging

Proposal (APL x 1)



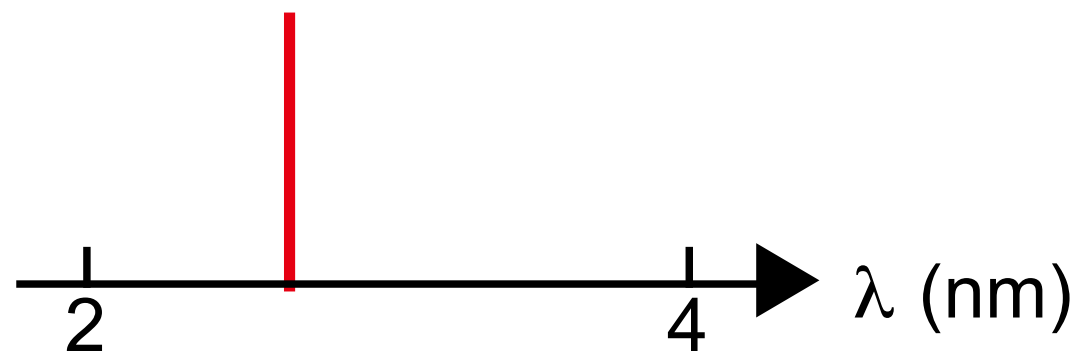
APL x 7
(2010-2012)

Quasi-Moseley's law...

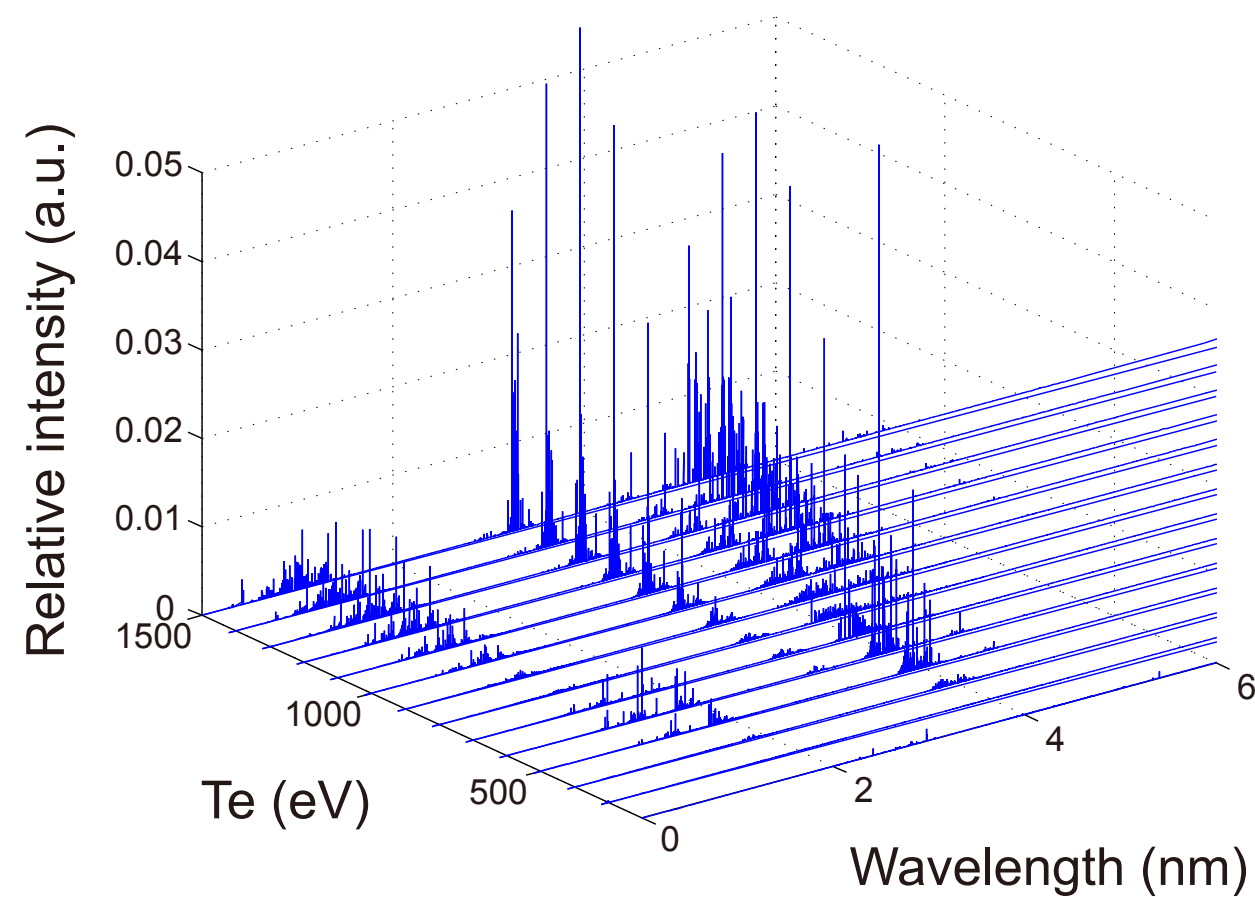
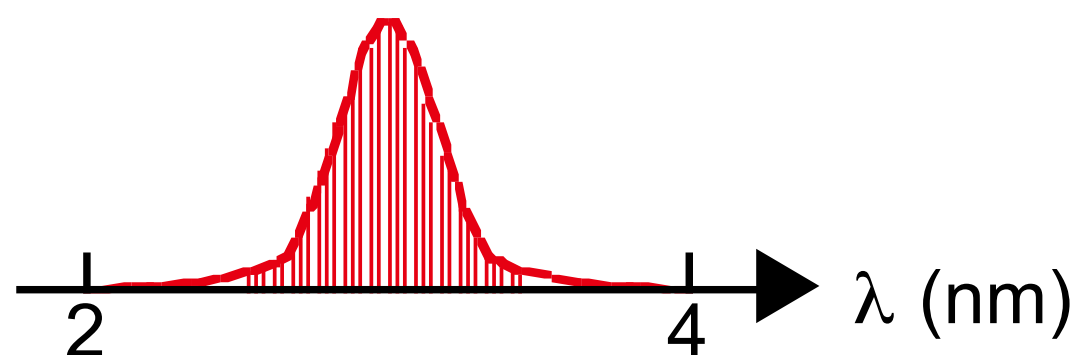


Concept for high CE WW flash source

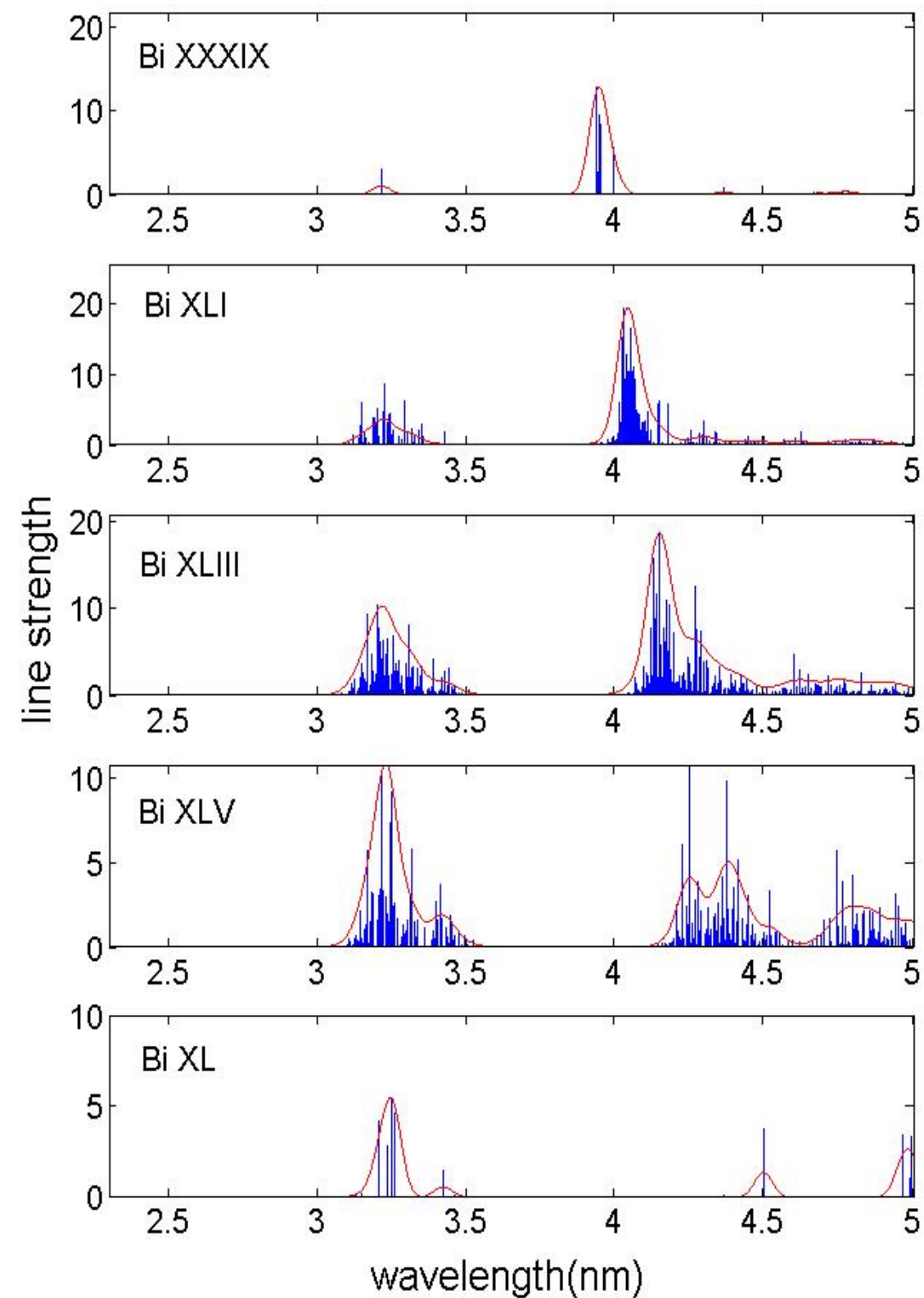
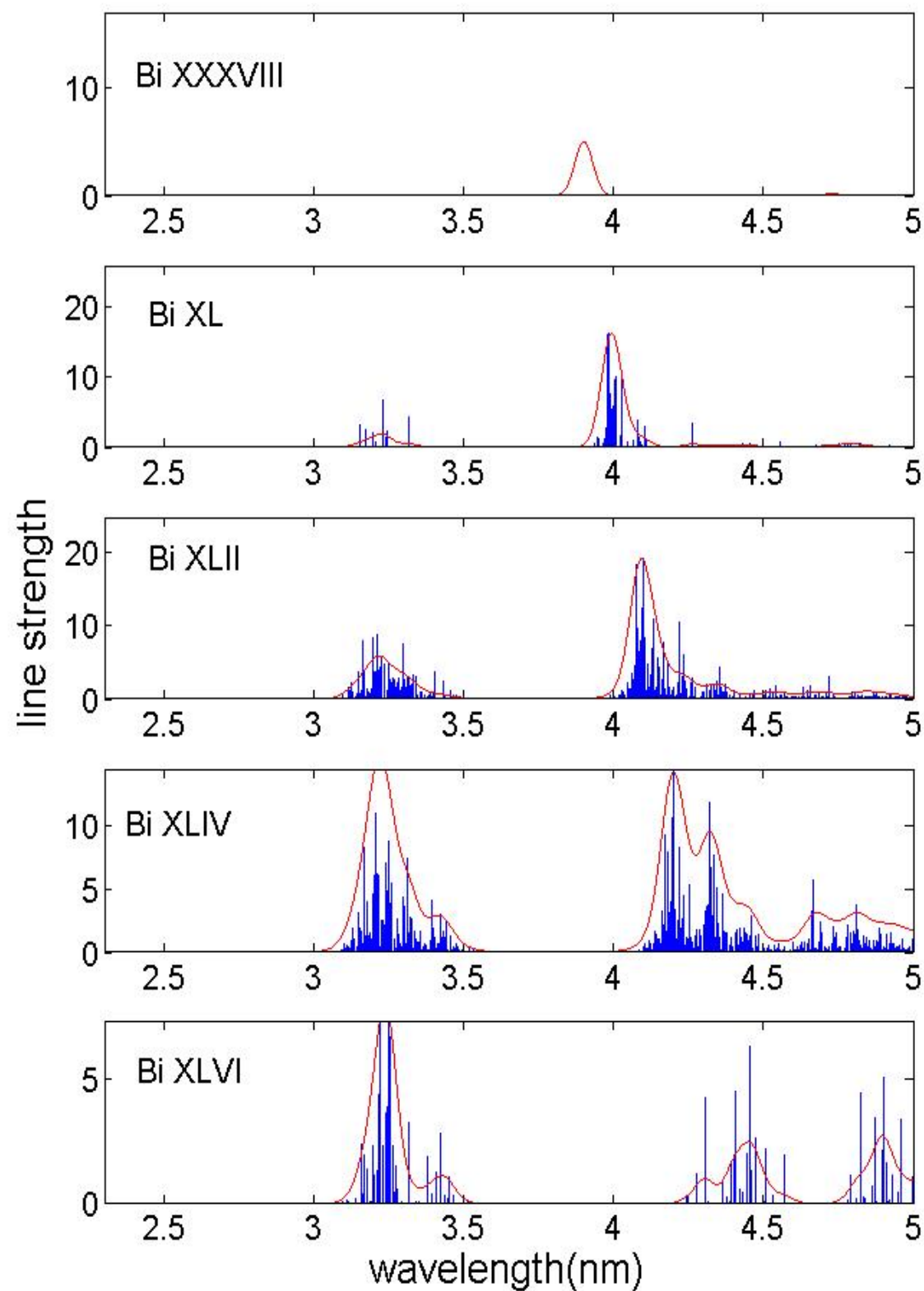
(a) Line spectrum



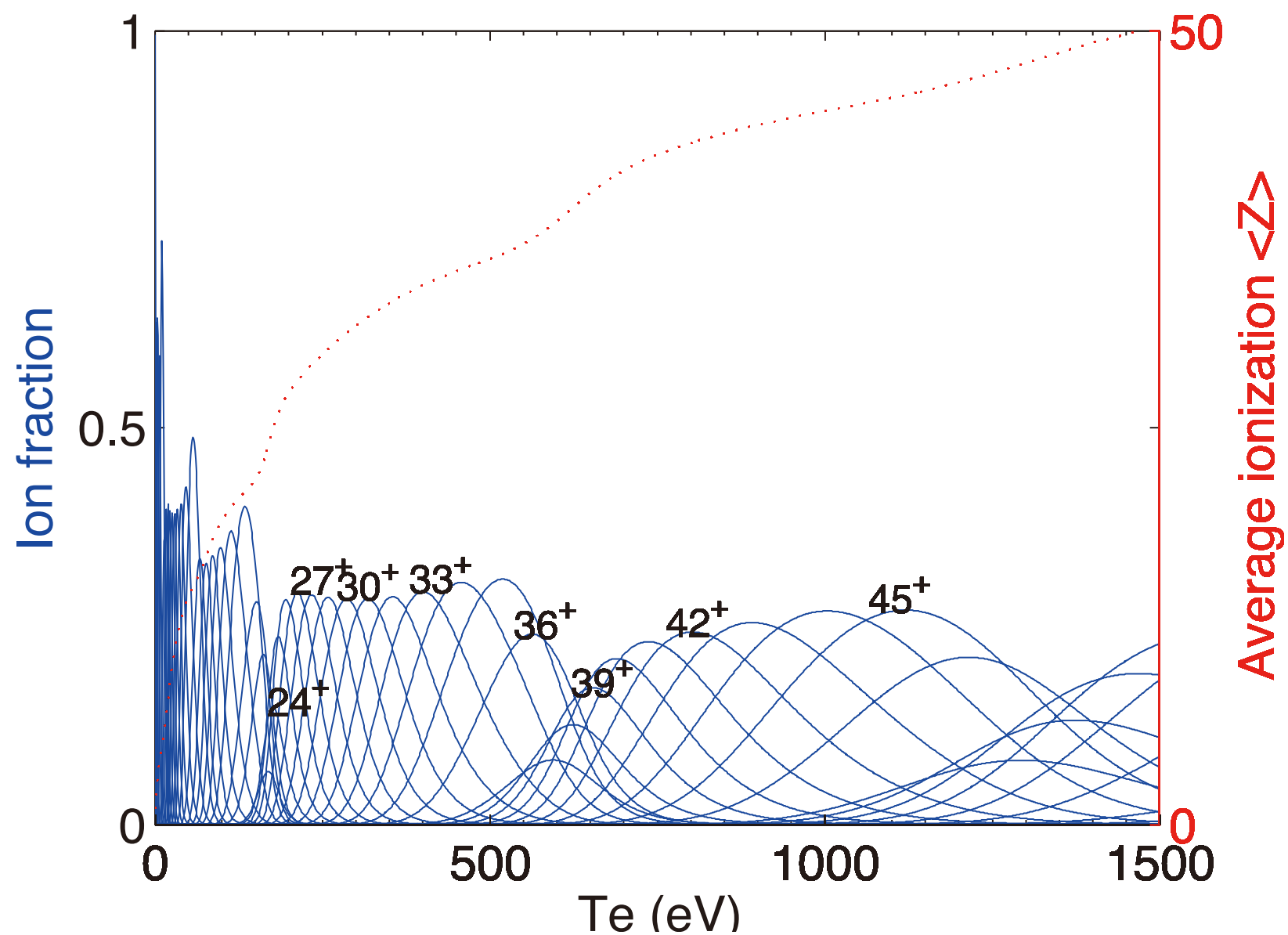
(b) UTA



Ionic charge state in **Bi**

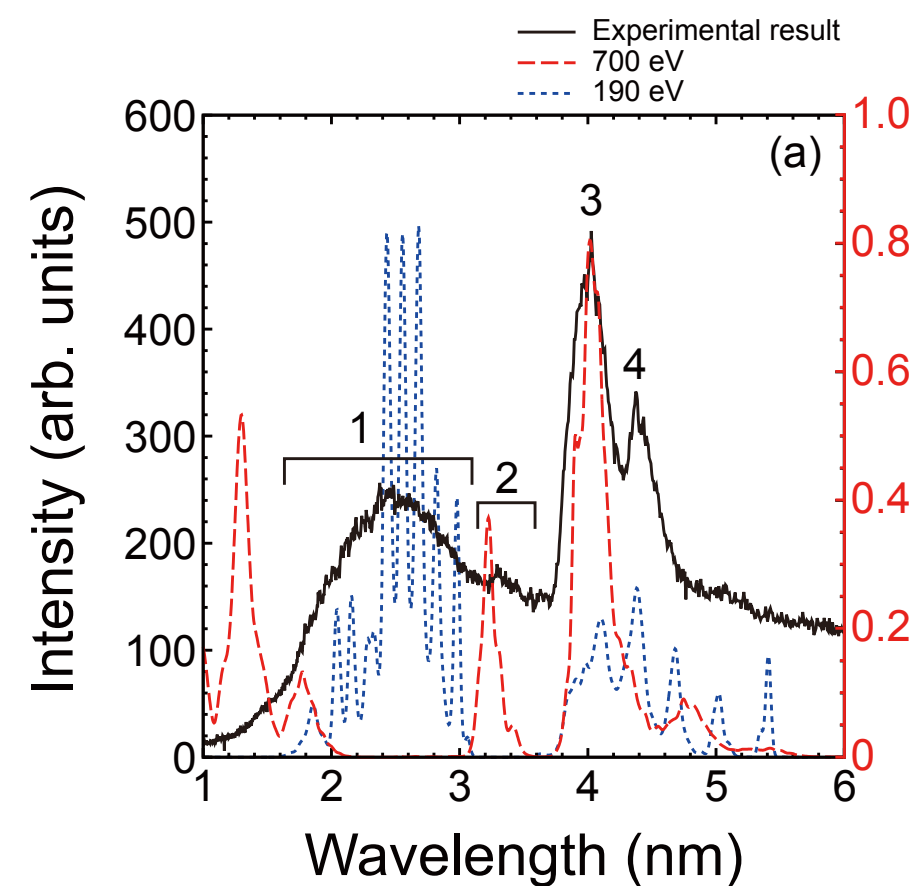
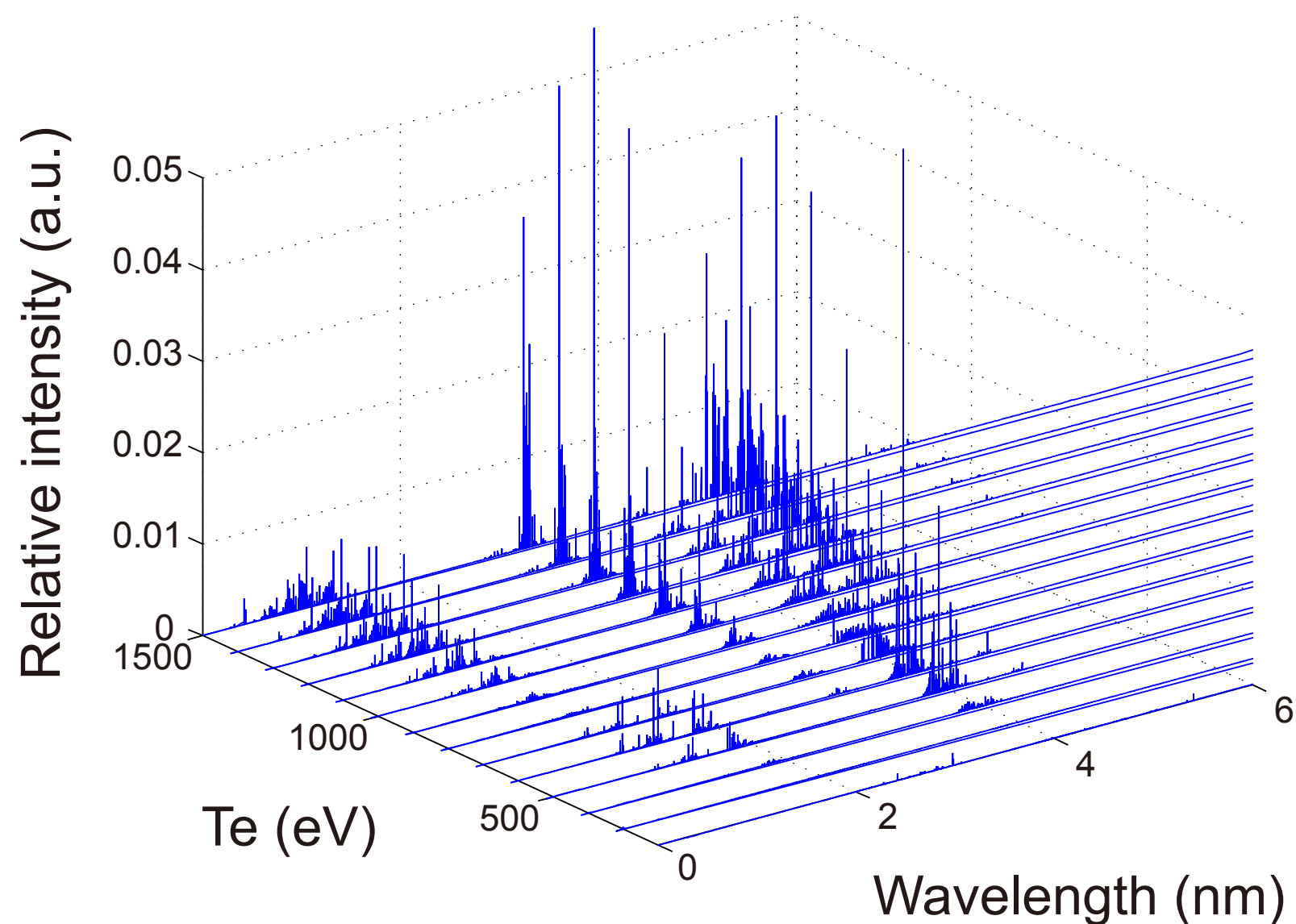


Optimum plasma temperature in Bi plasma: **1 keV**

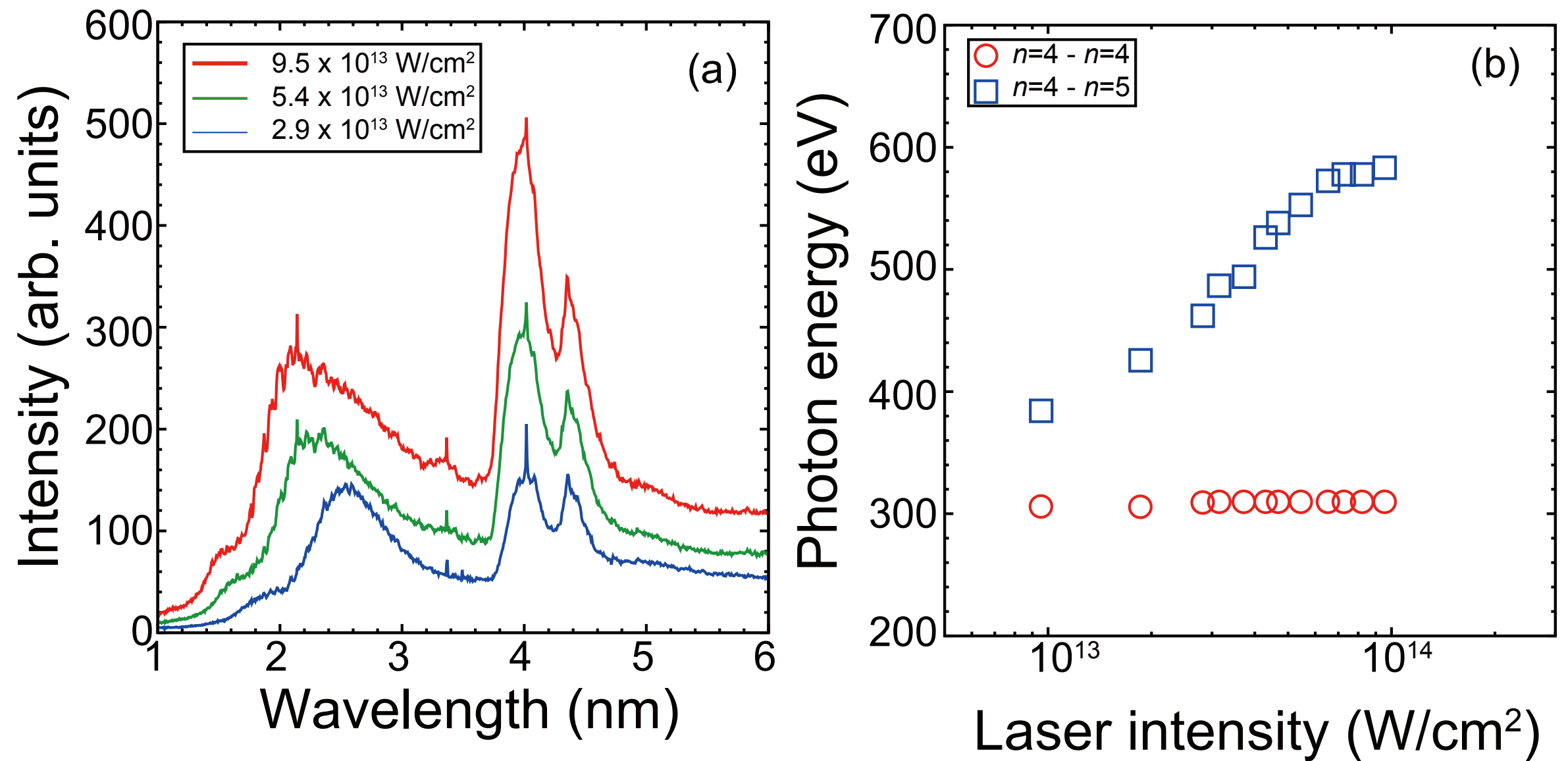


T. Higashiguchi *et al.*, Appl. Phys. Lett. **100**, 014103 (2012).

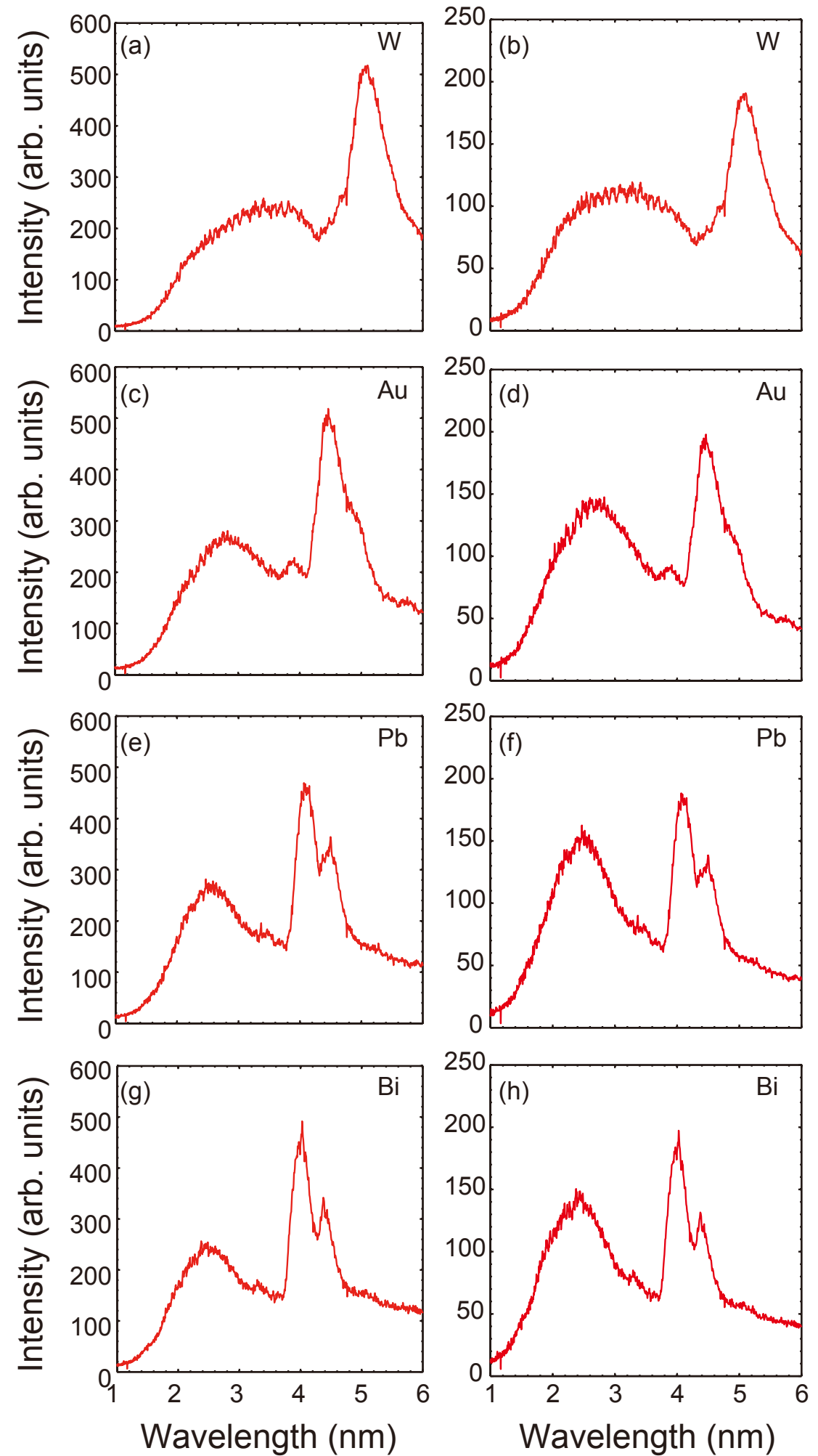
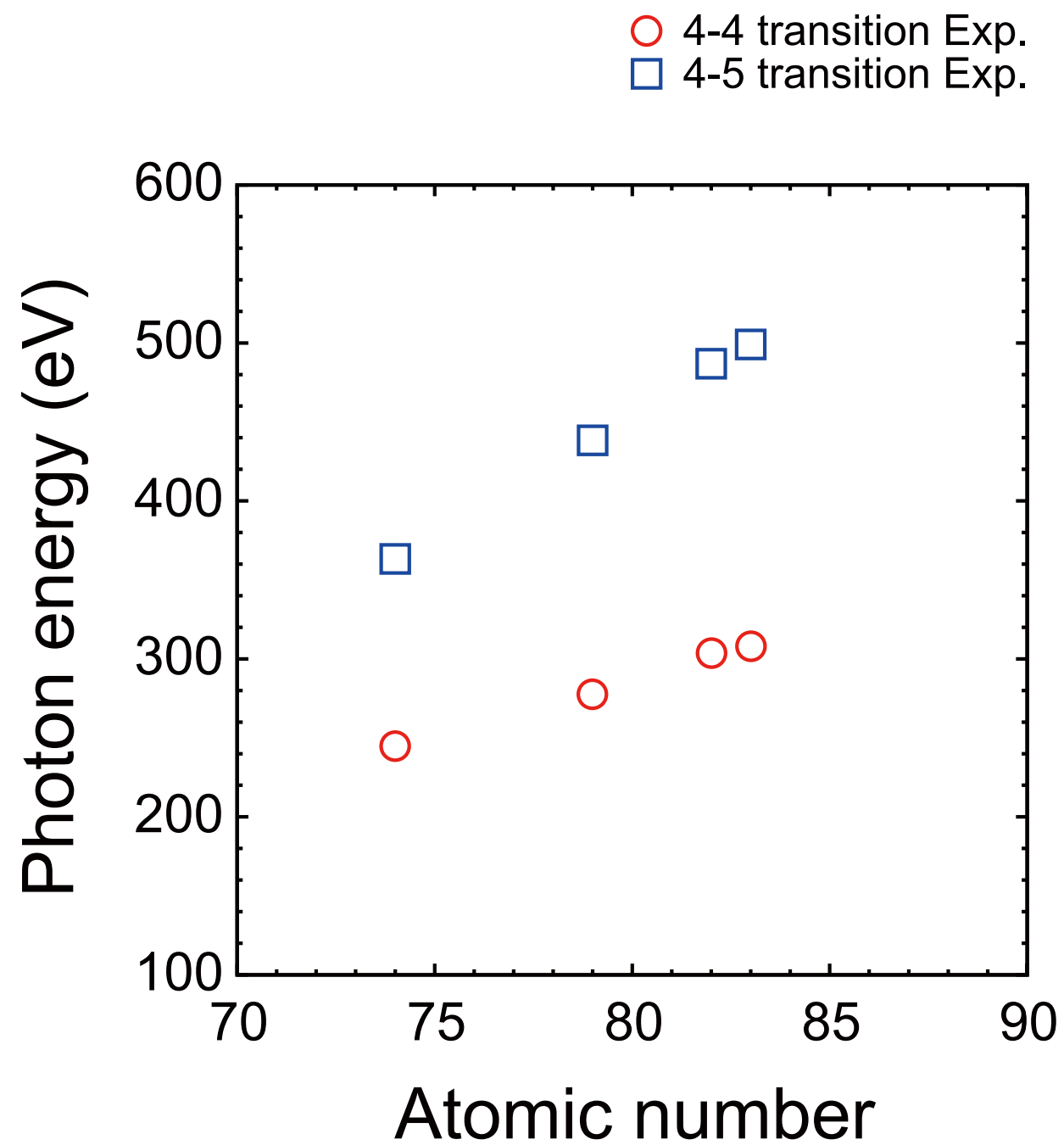
3-nm at high Temp. v.s **4-nm at low Temp.**



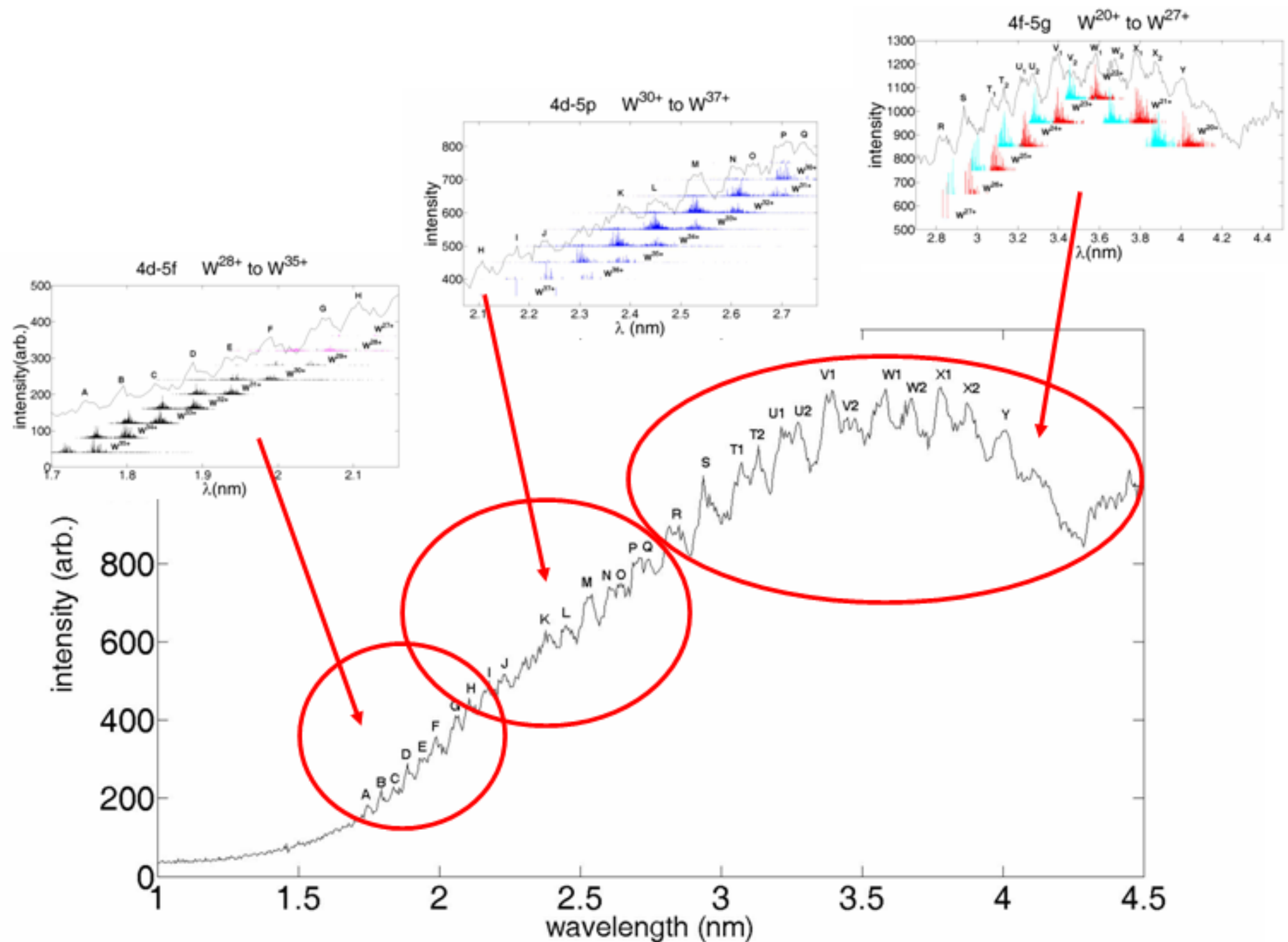
Laser intensity dependence in Bi

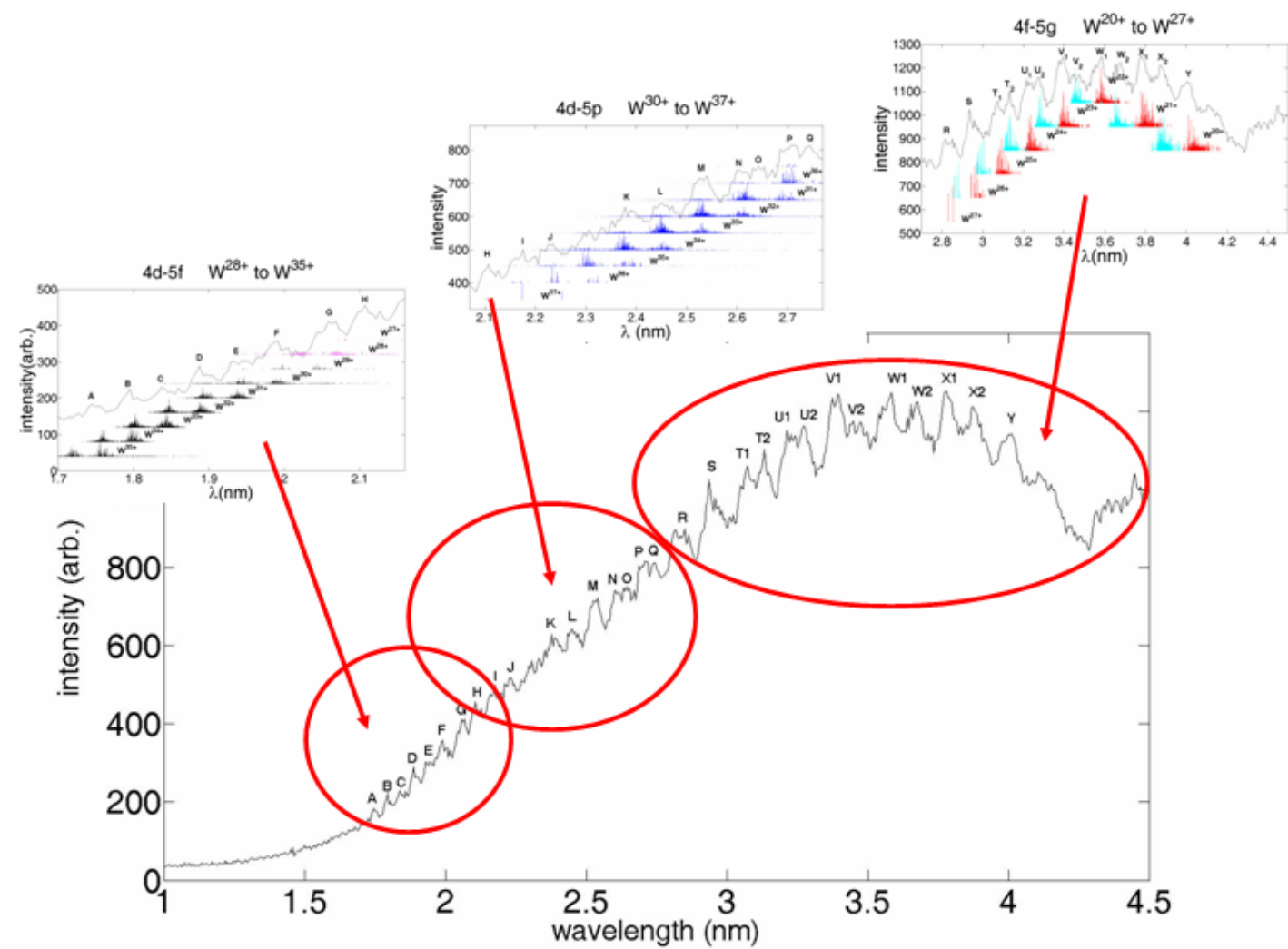
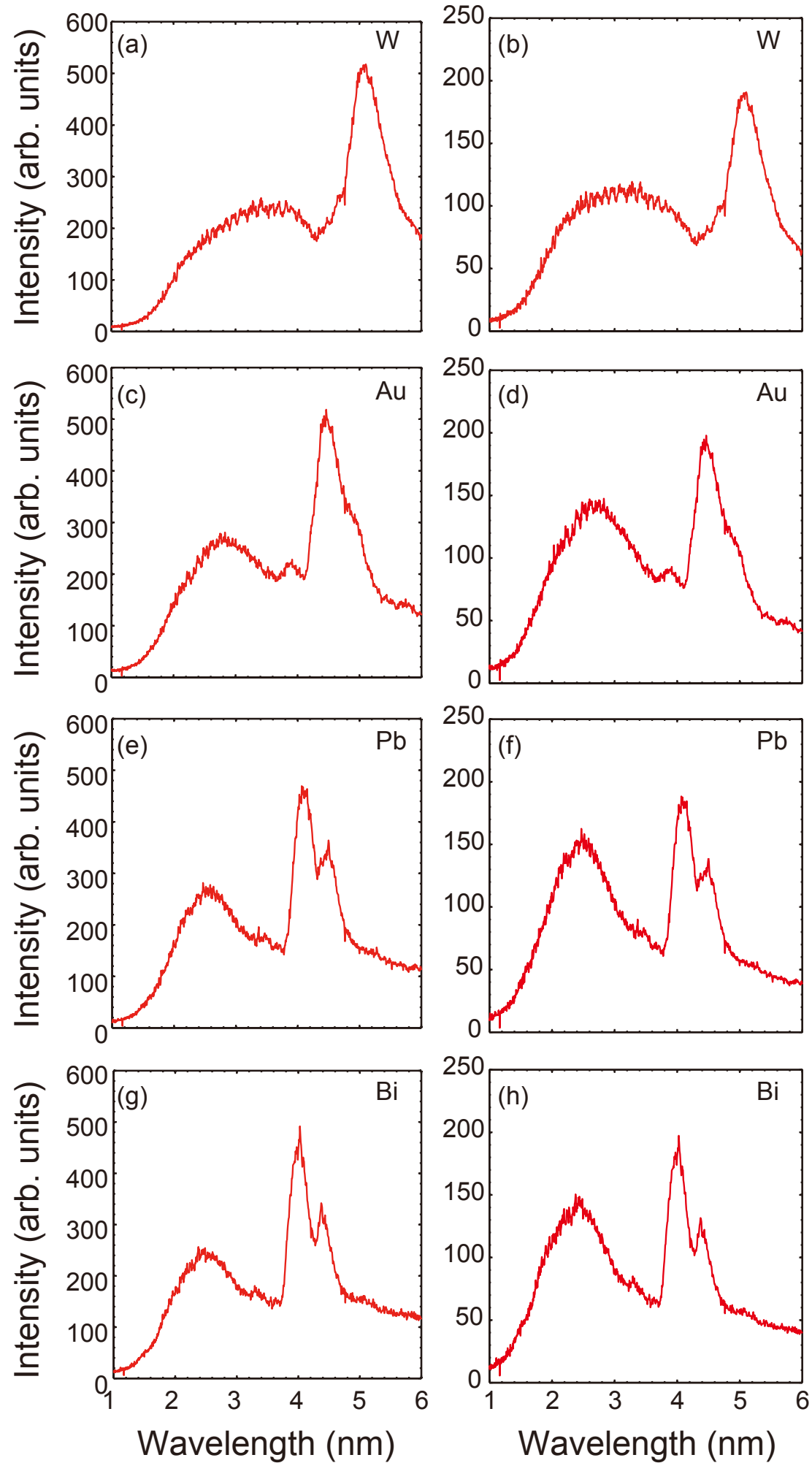


$n = 4-4, 4-5$ transitions



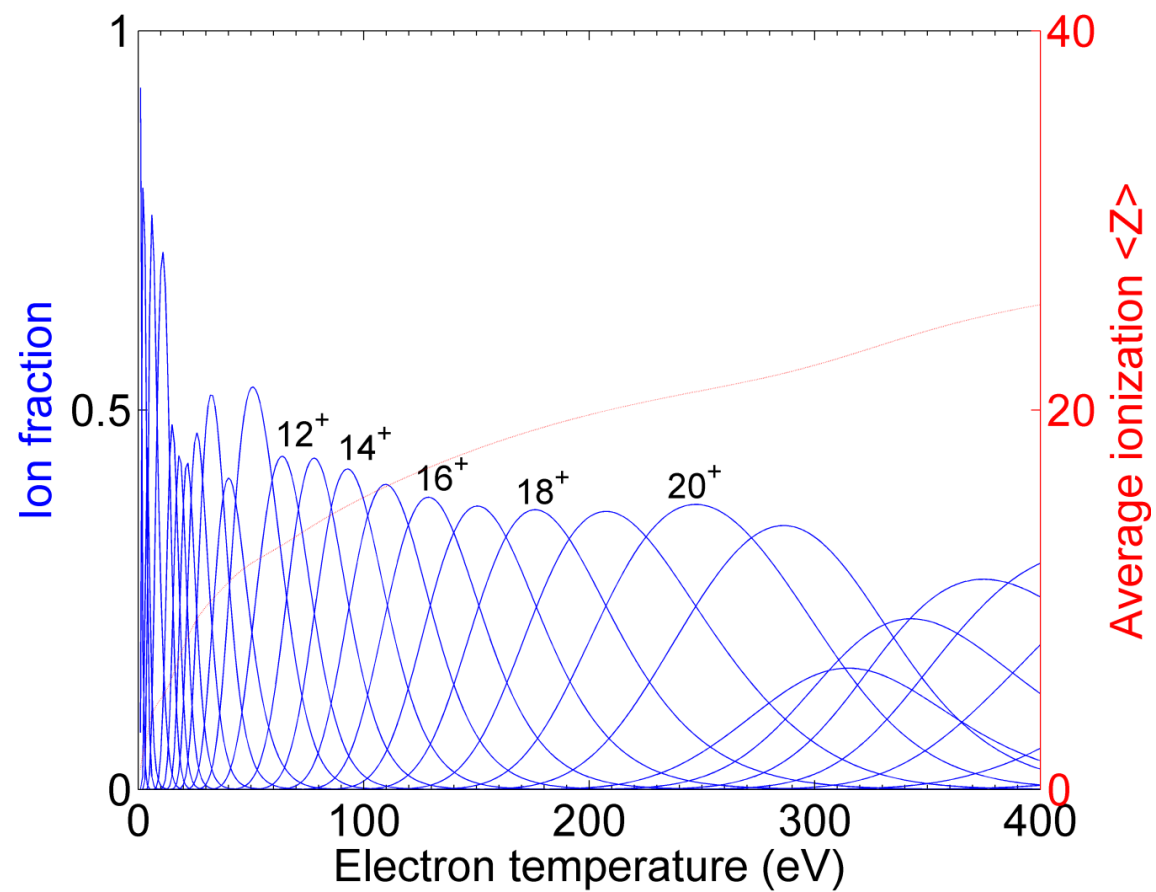
Water Window Spectrum from laser-produced **W** plasma



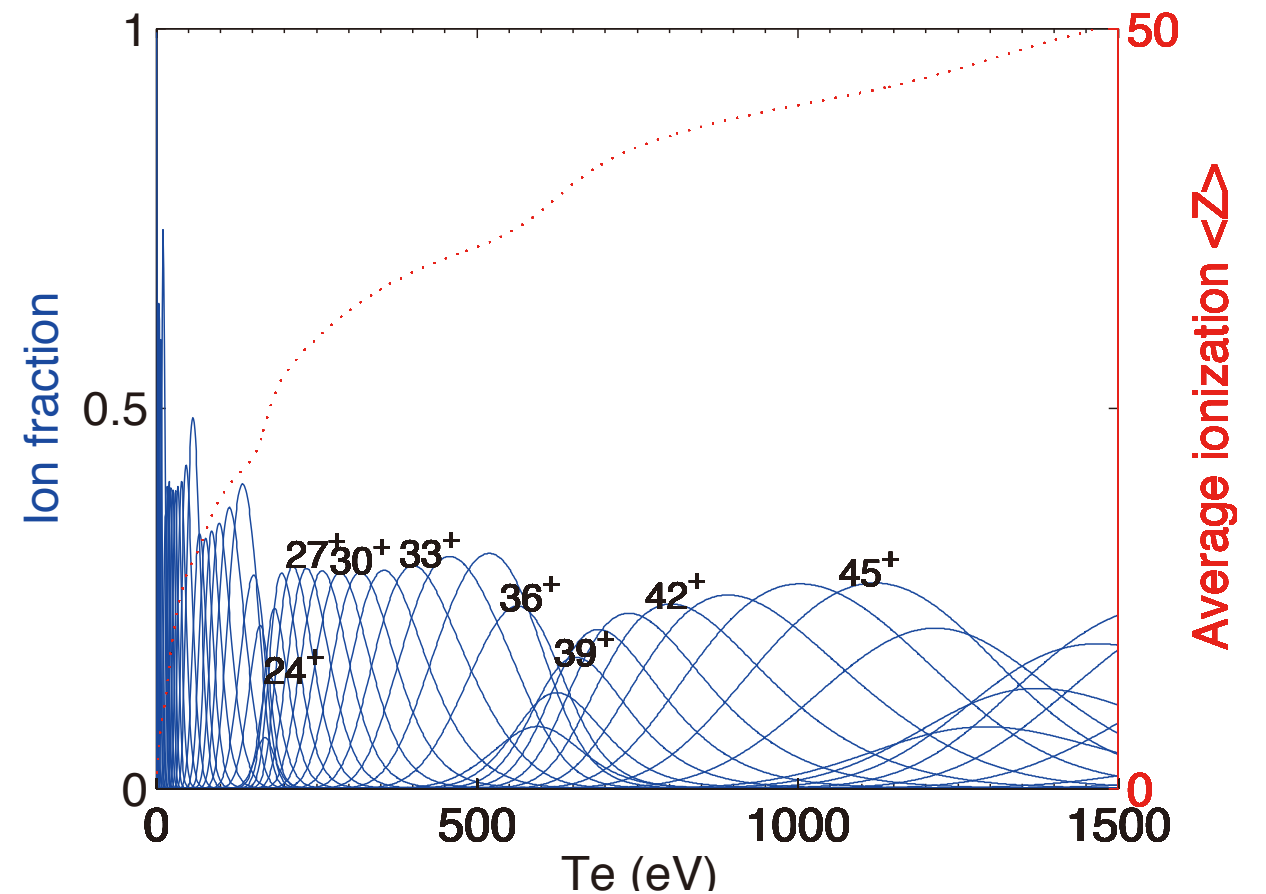


Lower temperature $\sim \mathbf{0.2}$ keV vs 1 keV

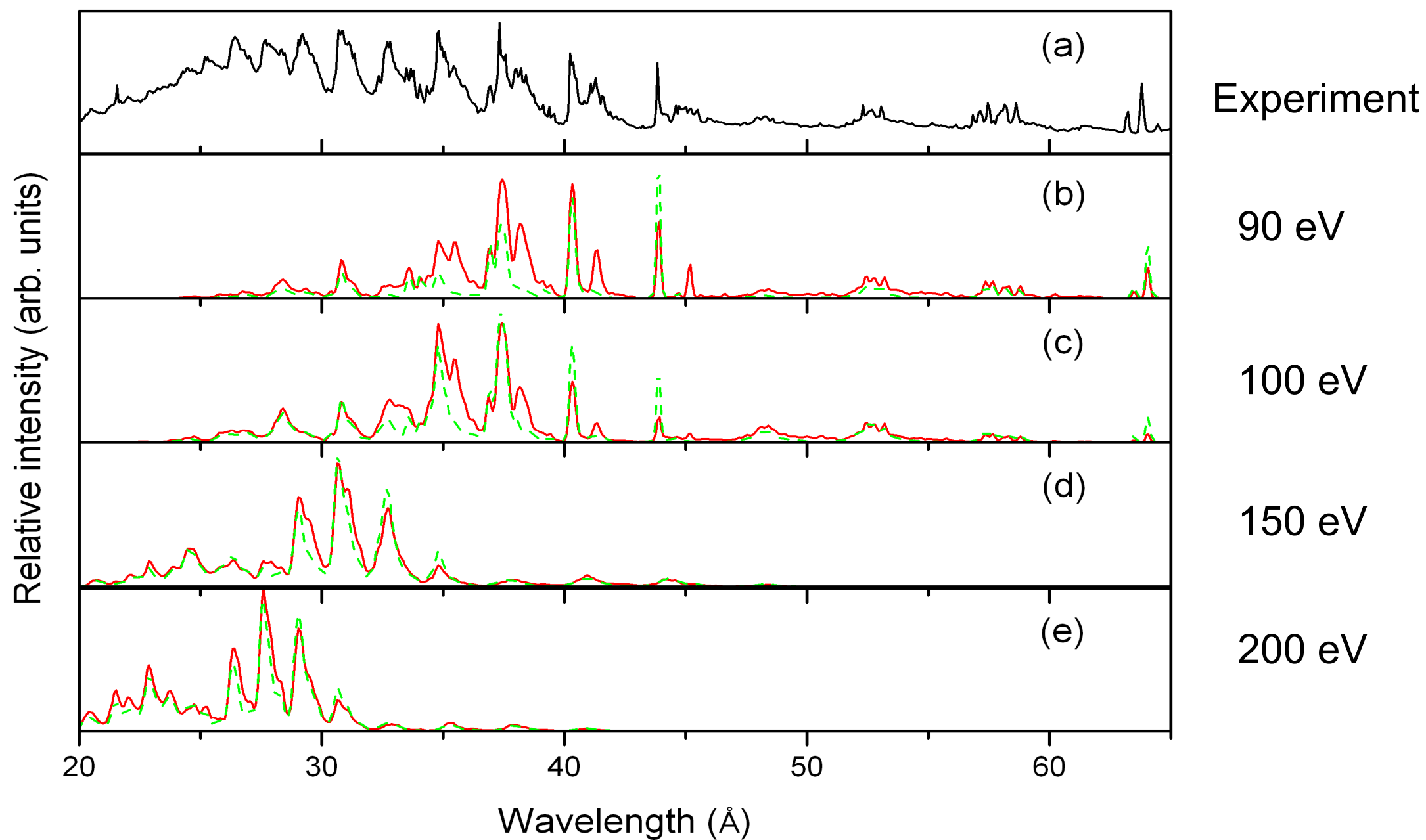
Zr



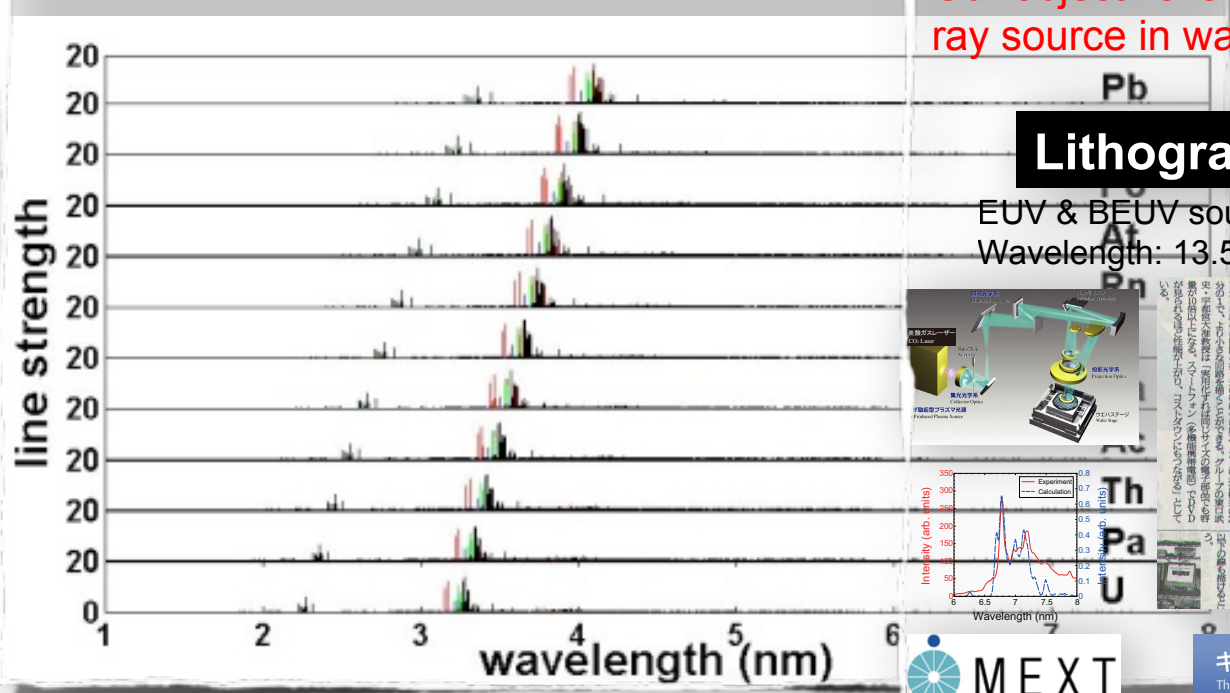
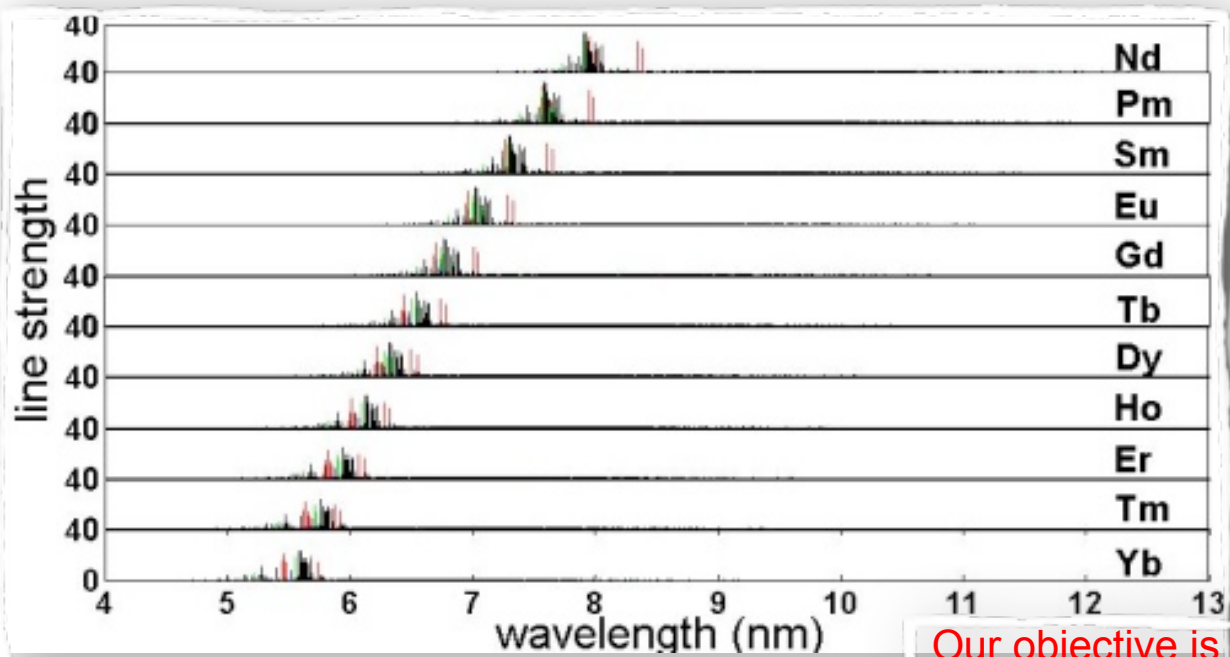
Bi



Recent Progress: **Zr** plasma WW source



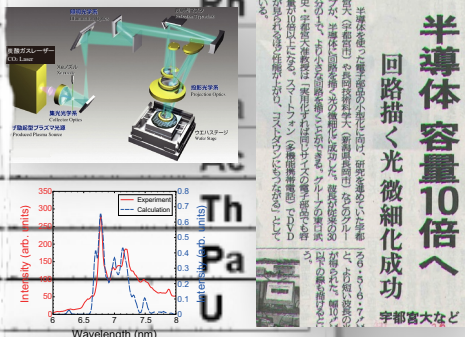
Summary



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EUV & BEUV source study
Wavelength: 13.5 & 6.x nm

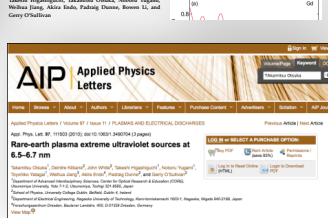


Shorter wavelength



Optical lithography: Lithography at EUV wavelengths

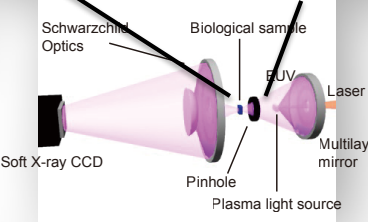
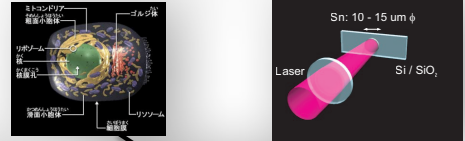
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